

Low-Loss Infrared Metamaterials: New Architectures and Unconventional Materials

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Outline

- Metamaterials: Design rules and functionality
- A lithographic approach to 3-D structures
- Unconventional materials for IR metamaterials
 - Polaritonic materials
 - Structure-property relations in MgO thin films
- Strategies for low loss metamaterials
 - Dielectric resonators



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Concept of Metamaterials

Electromagnetic Properties

ϵ – permittivity – measure of electric polarizability – electric charge separation

μ – permeability – measure of the magnetic polarizability – charge circulation

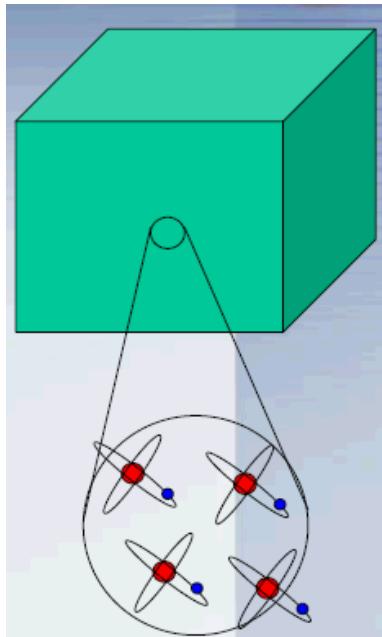
Index of refraction

$$n = \sqrt{\epsilon\mu}$$

Natural Material

ϵ – polarizability

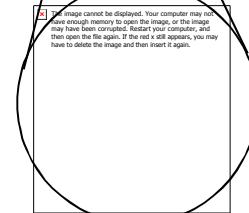
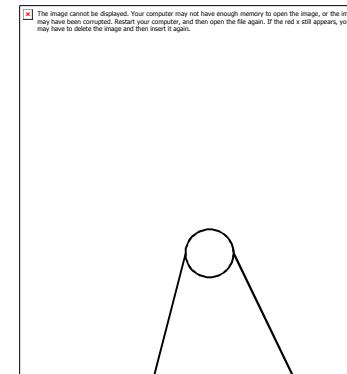
μ – QM spin



Metamaterial

ϵ – constituent material ϵ

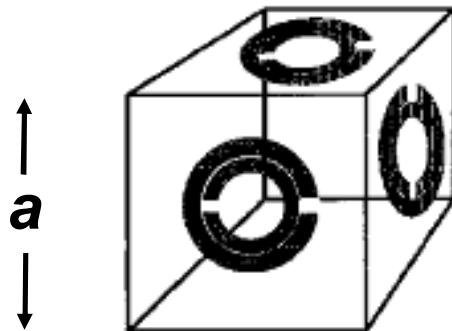
μ – induced charge circulation



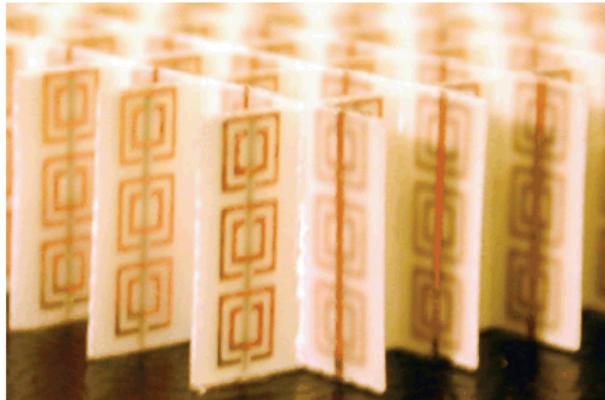


3D Metamaterials

- 3D is “easy” in the RF
- Would like to make the same structures in the IR



Pendry, IEEE Trans on Microwave Theory and Techniques **47**, #11, 2075 (1999)



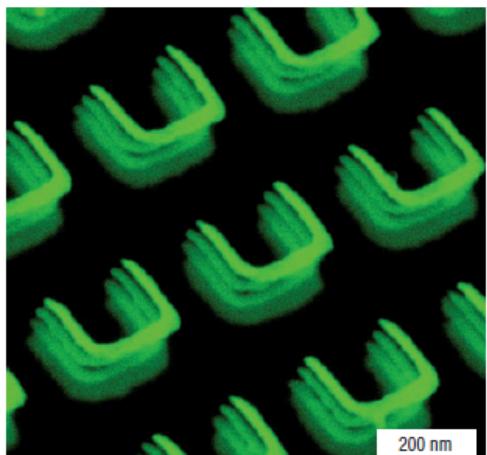
Schultz, Science **292**, 77, (2001)

- Geometrically isotropic cubic unit cell.
- Unit Cell Dimensions \sim cm
- Trace Linewidths \sim mm
- SRRs oriented along each coordinate axis

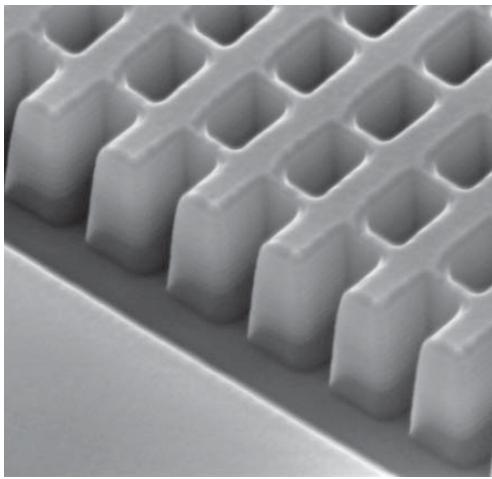


Current State of the Art in IR 3D MM fabrication

Stacked Planar

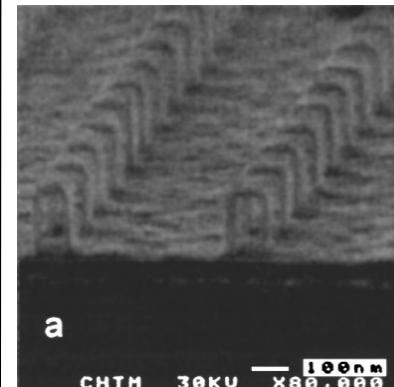


Giessen- Nat. Mater. 7, 31, (2008)

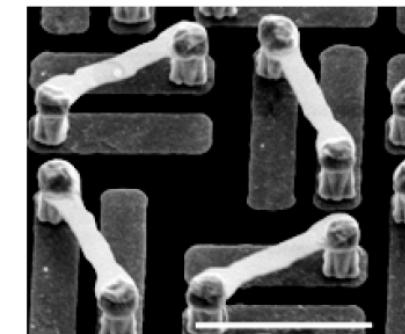


Zhang, Nature 455, 376 (2008)

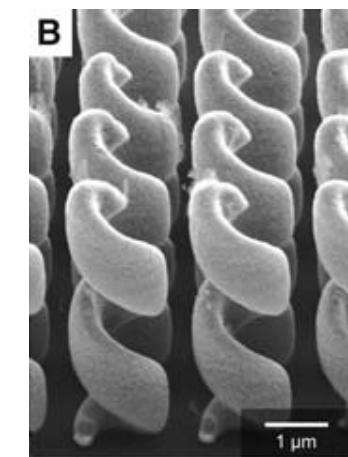
Out-of-Plane Current



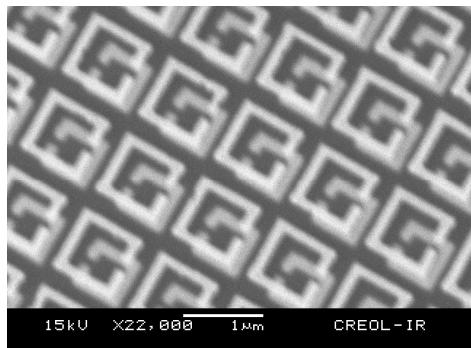
Brueck - JOSA B 23, 3
434, (2004)



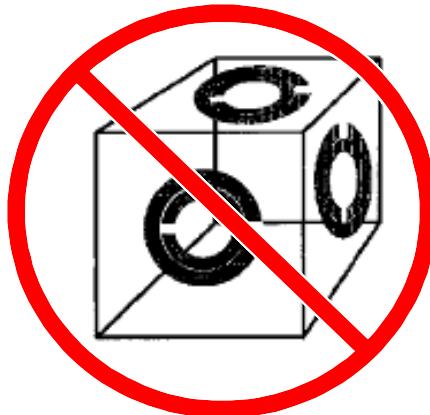
Zhang, PRL 102, 023901, (2009)



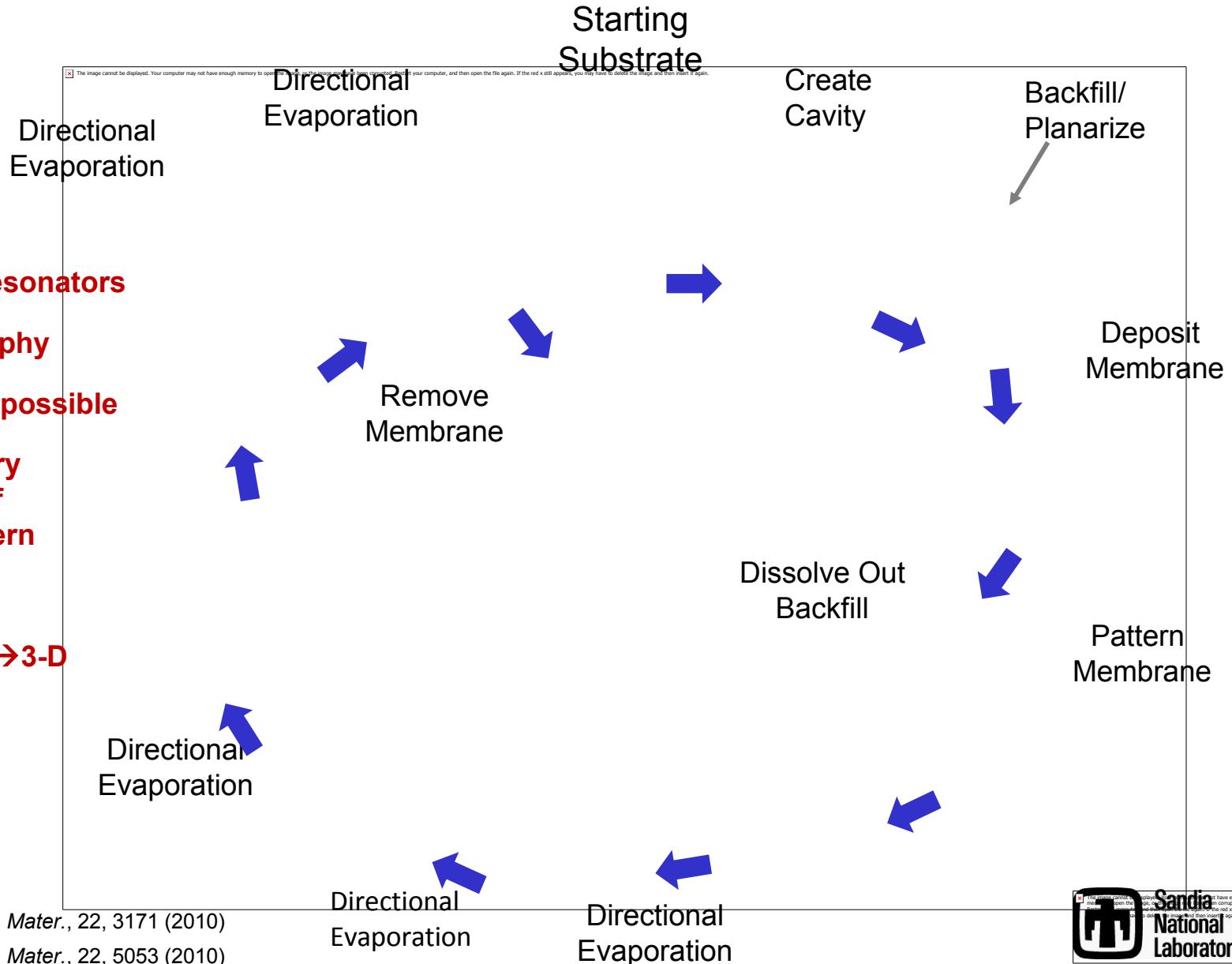
Wegener, Science 325, 1513-1515, (2009)



SANDIA+CREOL



Membrane Projection Lithography: MPL





3D Membrane Projection Lithography (3D MPL)

Evaporations

One to **Five**
(Normal + 4
Angled)

Pattern

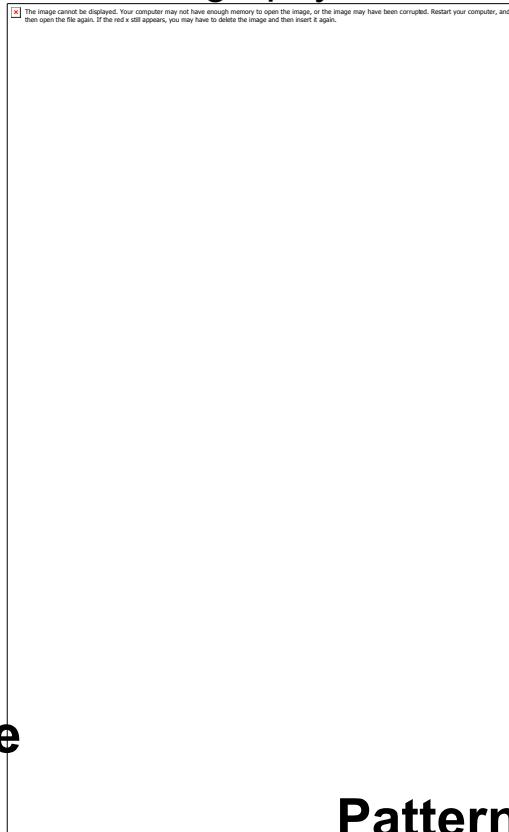
SRRs
Any non-closed loop,
structurally stable
design

Substrate

Silicon
Quartz
GaAs
BaF

Cavity formation

Optical lithography
Lithography + etch



Cavity shape

Cube
Cylinder
Grating

Lattice material
SU-8
Polyethylene

Backfill

Polyimide
SU-8
Oxide

Membrane

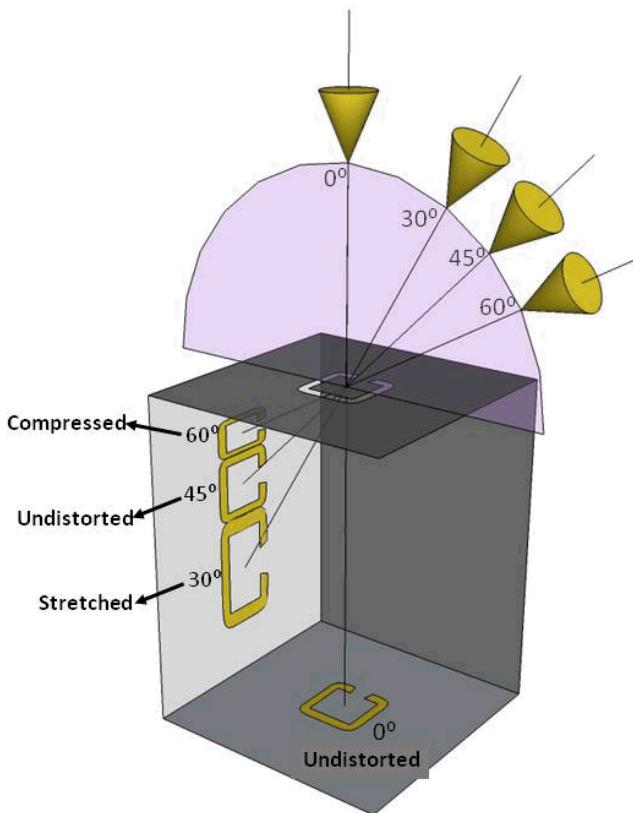
PMMA
Positive/Negative resist
hardmask (oxide, nitride)

Pattern Lithography

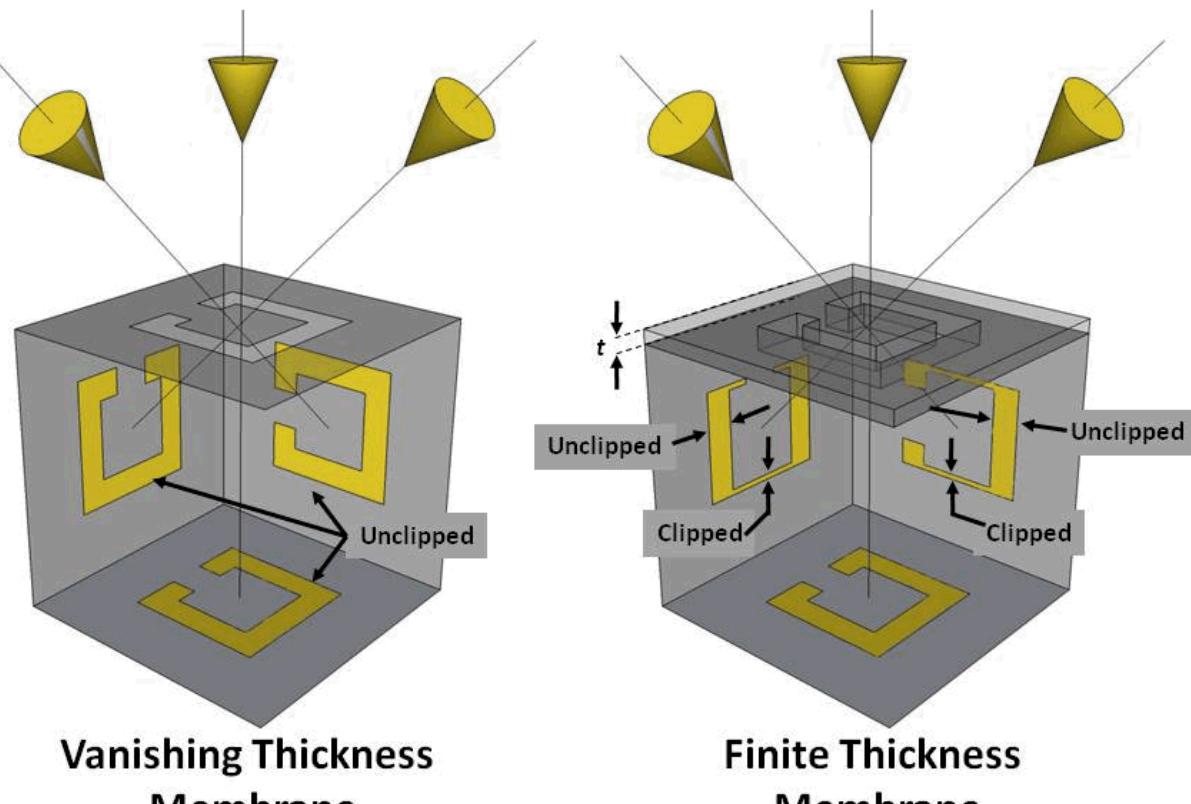
E-beam (JBX-9300FS)
Optical
Interferometric

Sources of Pattern Distortion

Projection at 45°
Preserves Pattern
Shape in Cubic Geometries

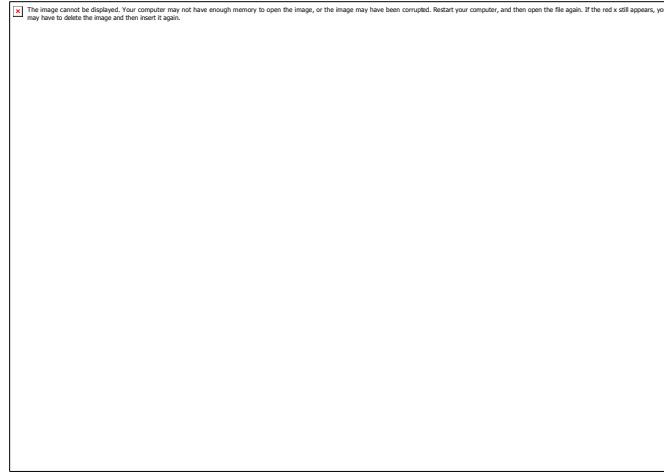
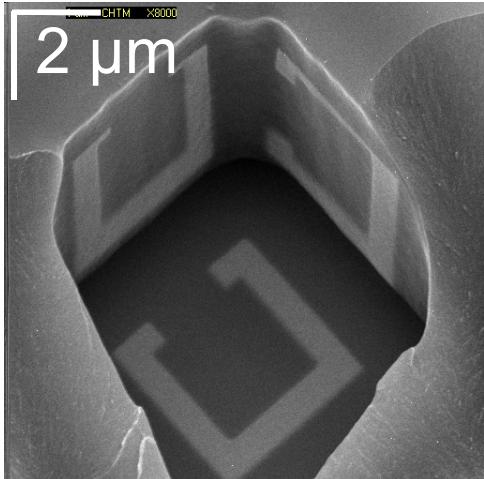
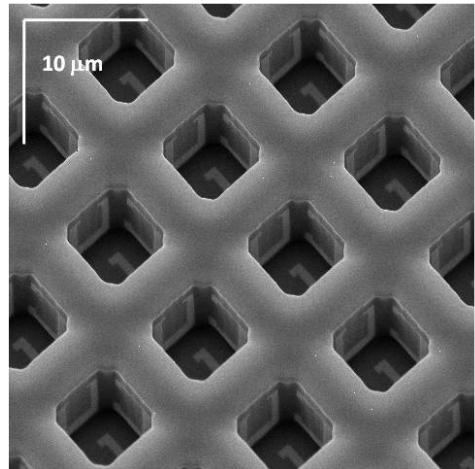


Real Membranes result in Linewidth Clipping

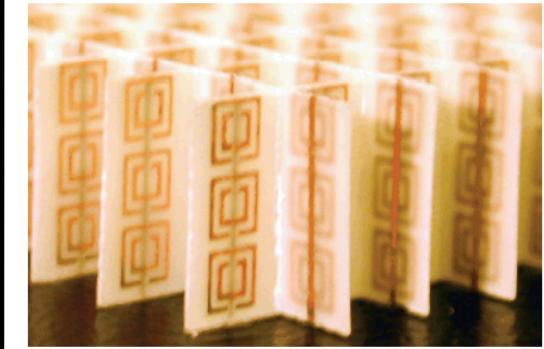


- Least distortion with thin membranes
- Can pre-compensate membrane pattern

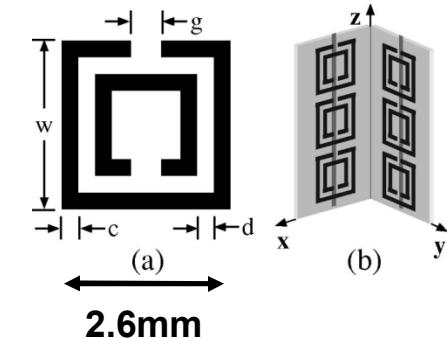
Cubic 3D Metamaterials via MPL



For Reference



Schultz, Science 292, 77, (2001)

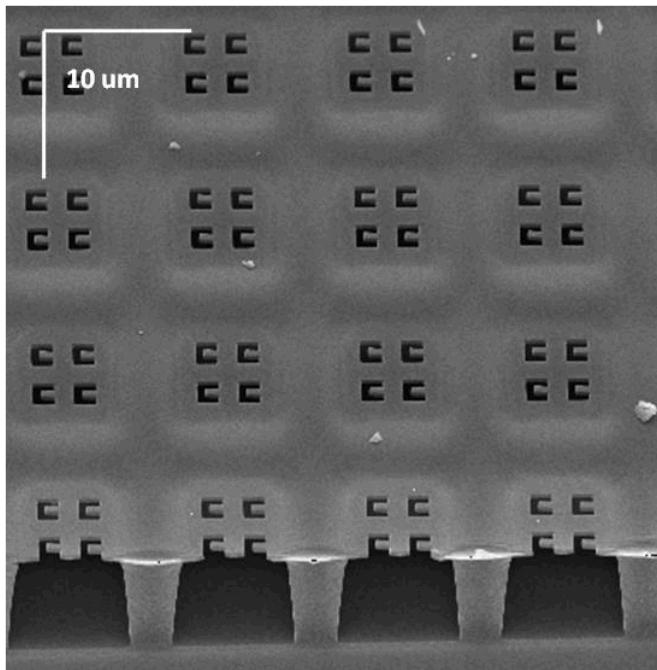


- Unit Cell Dimension = 14 μm pitch
- SRR Dimension = 8 μm
- Resonance wavelength \sim 50 μm
- Unit Cell Dimension = 6 μm pitch
- SRR Dimension = 3 μm
- Resonance wavelength \sim 22 μm

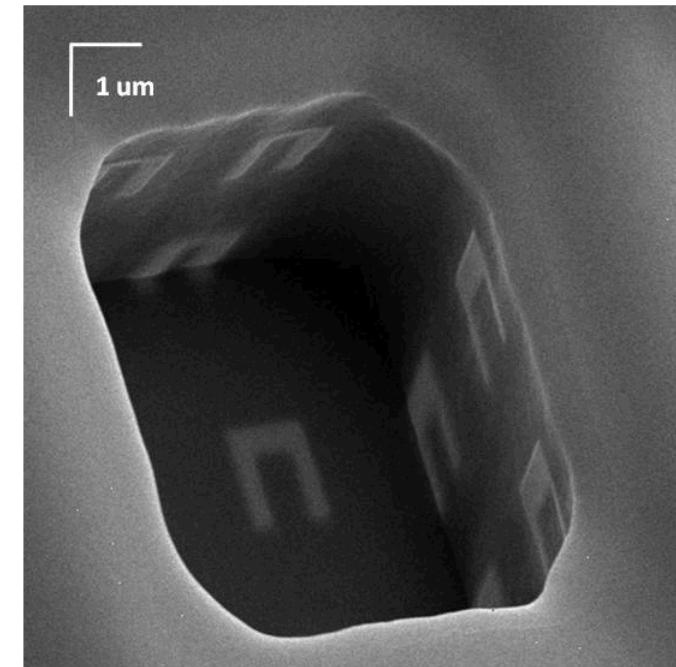
- Unit Cell Dimension = 5mm
- SRR Dimension = 2.6mm
- Operating Wavelength = 3cm



More 3D MPL Fabrication Results

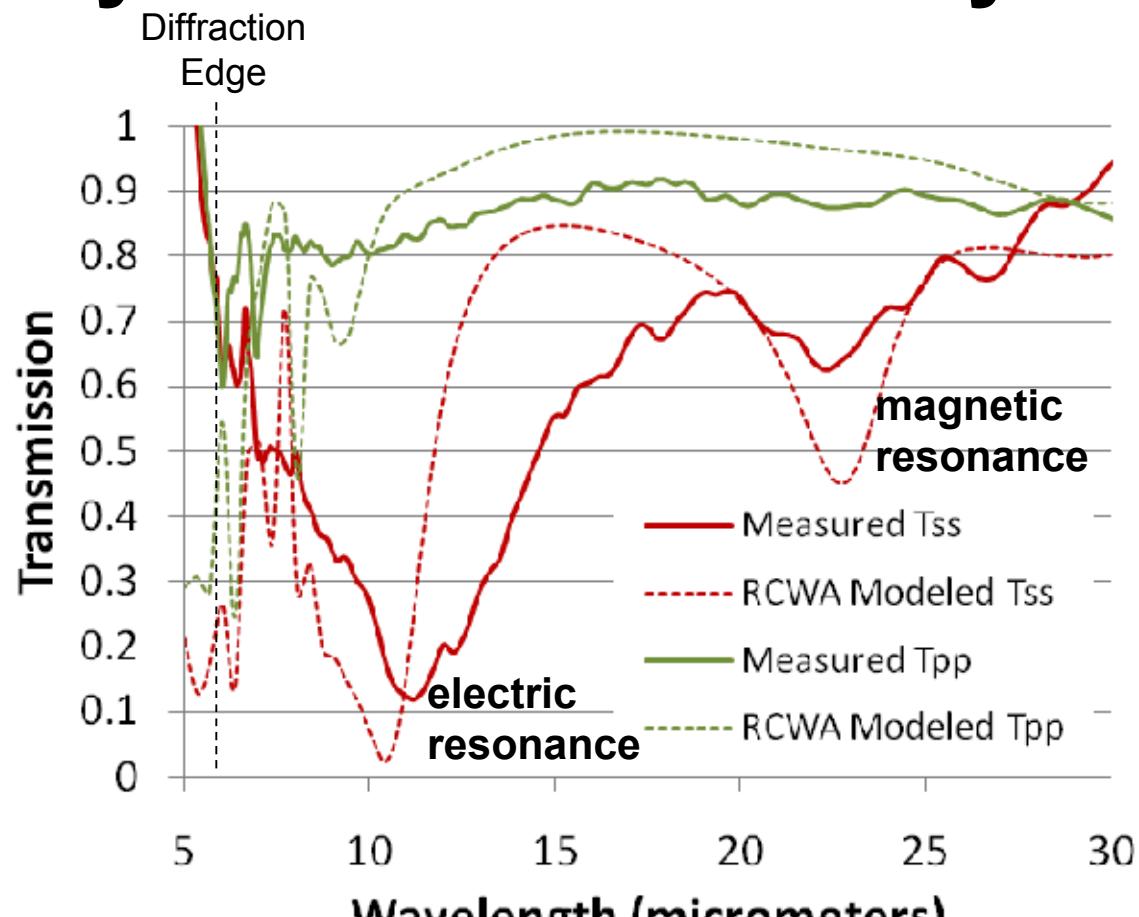
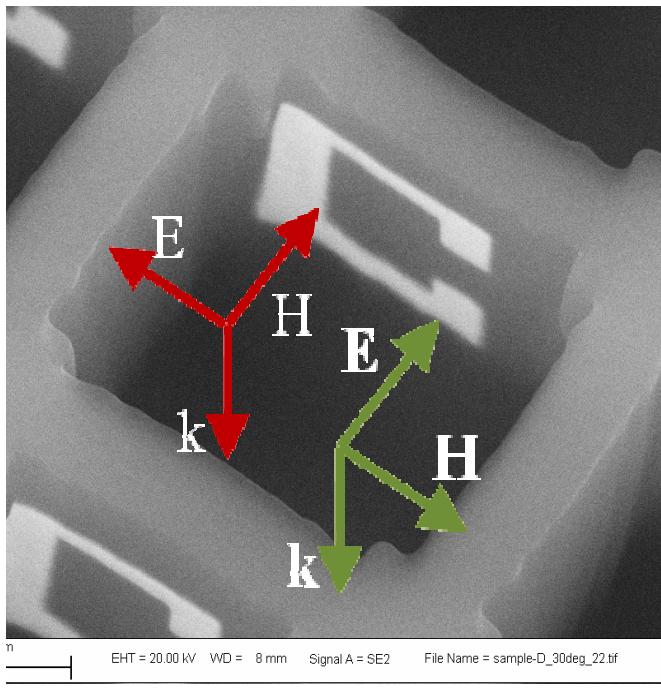


Patterned PMMA membrane suspended over and aligned to boxes formed in SU-8.



- Gold SRR patterns deposited onto the five box surfaces after liftoff.
- Predictable distortions of the patterns on the vertical walls.

Polarized Transmission of Magnetically Excited SRR Array



S-polarization

- B -field excites lowest SRR resonance --- magnetic excitation
- E -field excites second order resonance --- electric excitation

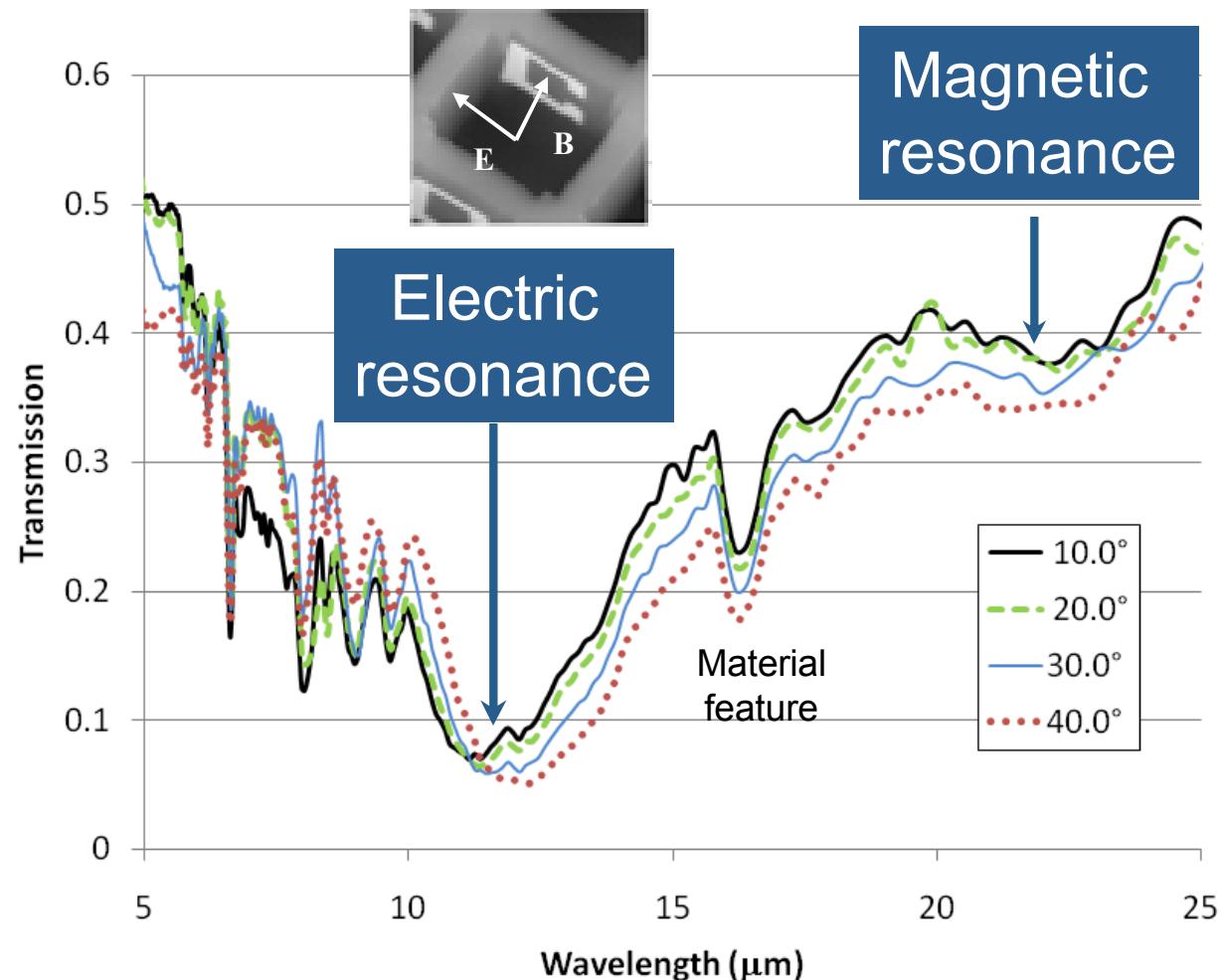
P-polarization

- can't couple to any SRR resonances

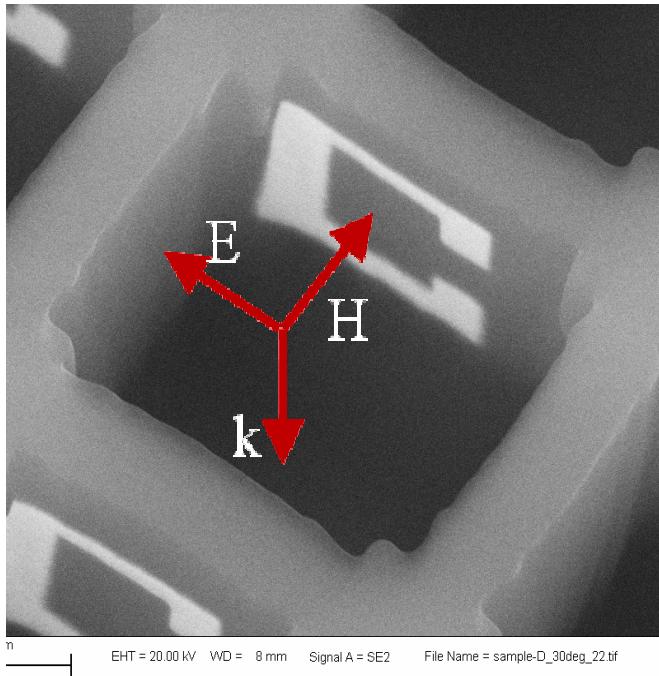
Angle Dependence of Spectral Response

Characterization Techniques

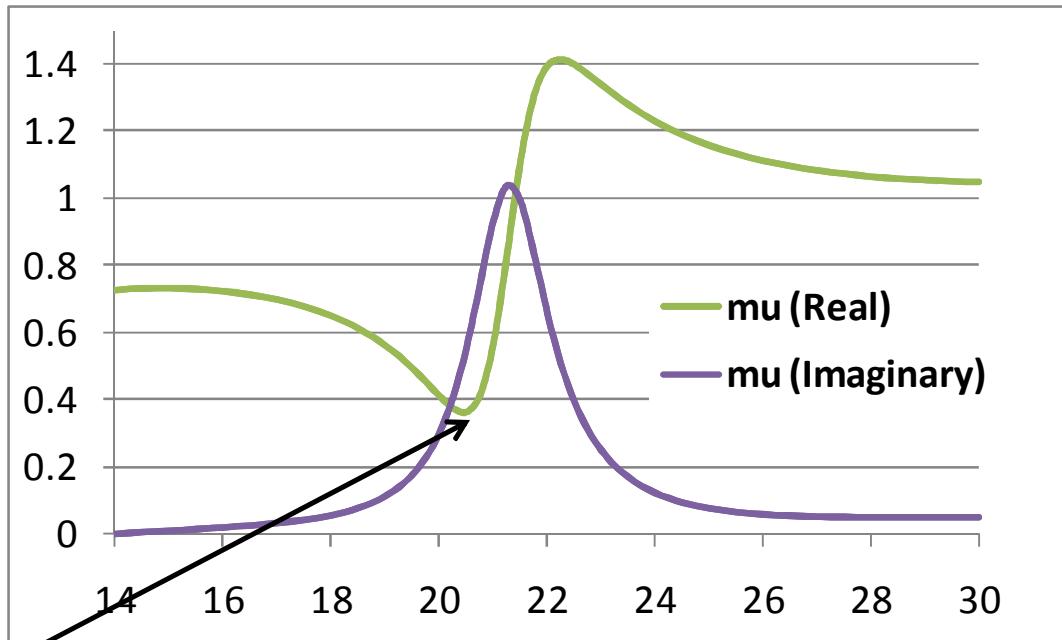
- Hemispherical
- Directional
- Transmission
- FTIR
- Variable Angle Spectroscopic Ellipsometer



Extracted permeability for modeled array with SRRs on single wall



$$\mu = 0.37 + i 0.56$$



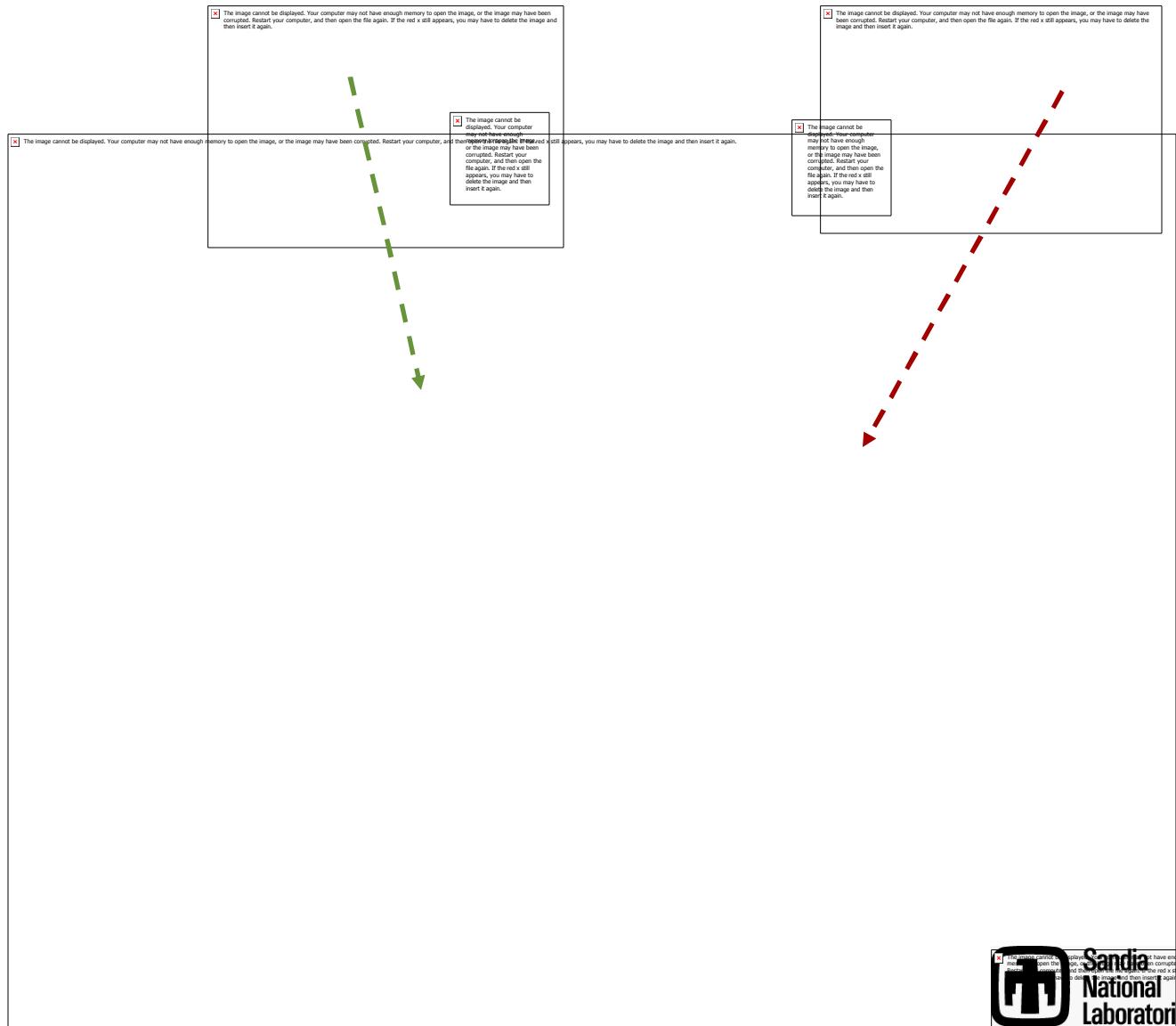
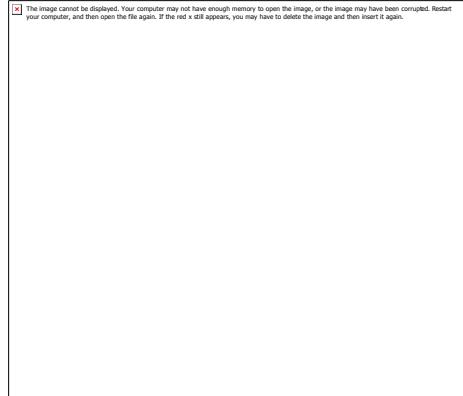
Optimized Q-factor for the resonator along with increased packing fraction is expected to improve the strength of the resonance and increase the range of permeability tuning

D.B. Burckel, et al.,
Adv. Mater., 22, 3171 (2010)
D.B. Burckel, et al.,
Adv. Mater., 22, 5053 (2010)



Polarized Transmission of 5-SRR Unit Cell

Composite SRRs

 T_{pp} T_{ss}

D.B. Burckel, *et al.*,
Adv. Mater., 22, 3171 (2010)

D.B. Burckel, *et al.*,
Adv. Mater., 22, 5053 (2010)

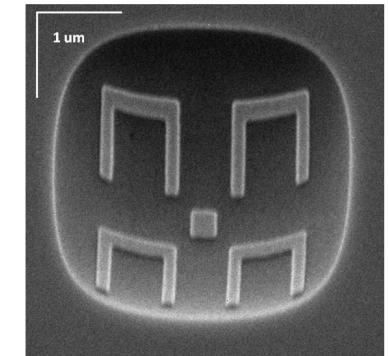
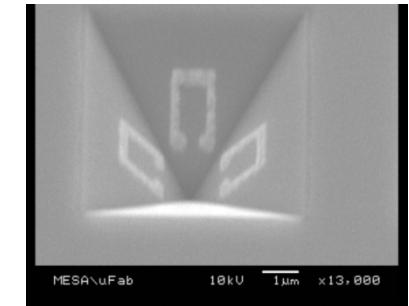
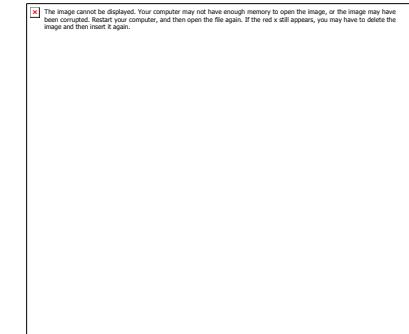
Summary & Future Directions

Membrane Projection Lithography (MPL) enables 3D metamaterials

- large area
- out of plane resonators
- can choose orientation & placement of resonators for desired excitation
- demonstrated magnetic response at normal incidence at $\lambda = 22 \mu\text{m}$

Currently:

- optimizing EM design for maximal response: higher Q therefore negative μ
- Begin exploring inclusion designs aimed at tuning permittivity (ϵ).
- currently on track to demonstrate multi-layer MPL and LWIR structures.

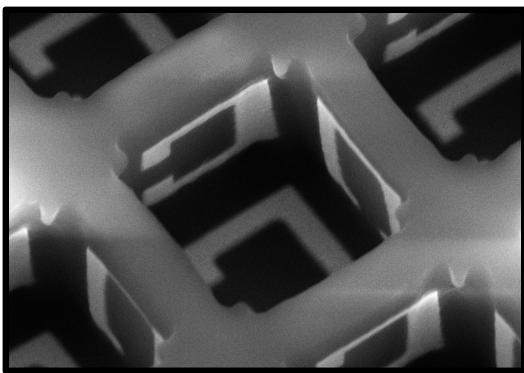




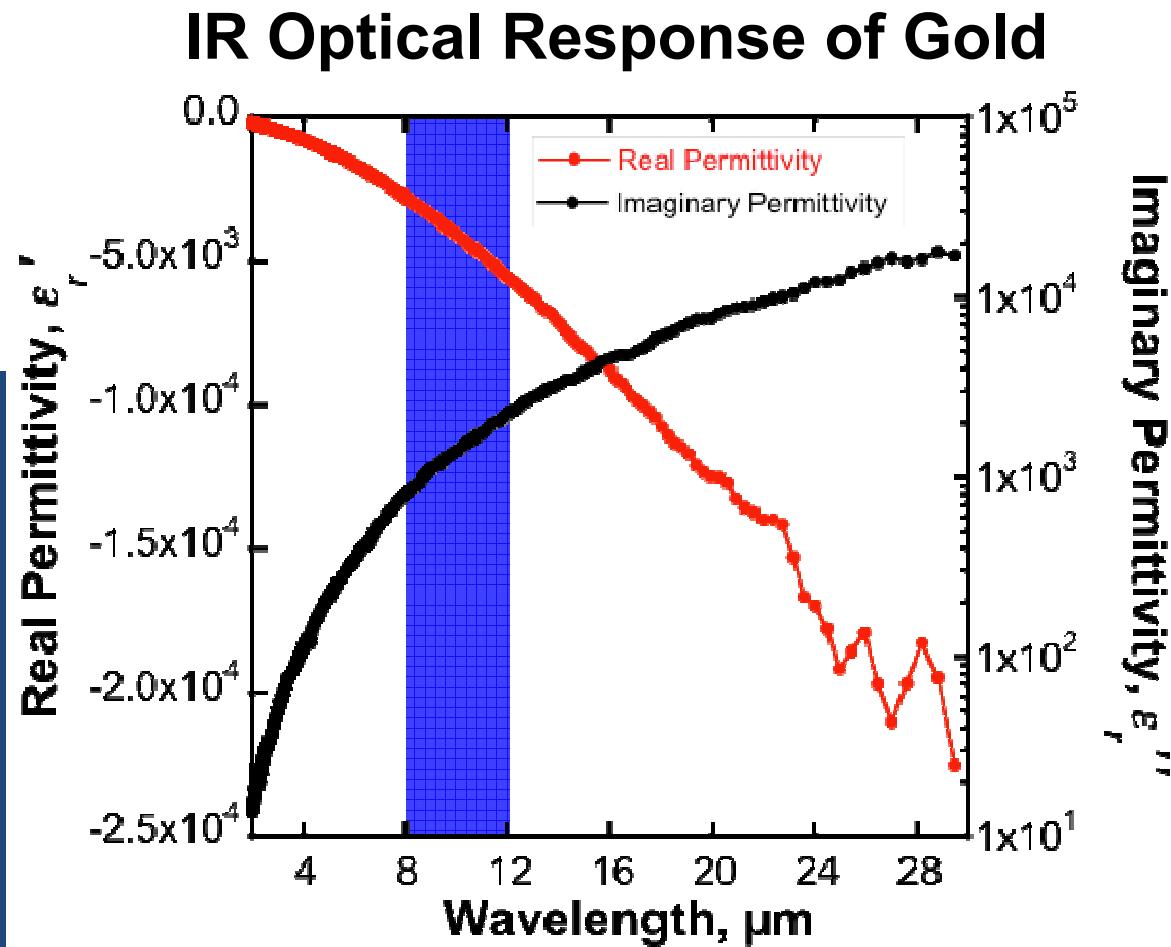
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Traditional Metamaterials:



- Traditional metamaterials designed with metallic elements
- Metal conductivity decreases substantially approaching optical frequencies
- Losses high in optical frequencies (Ohmic)

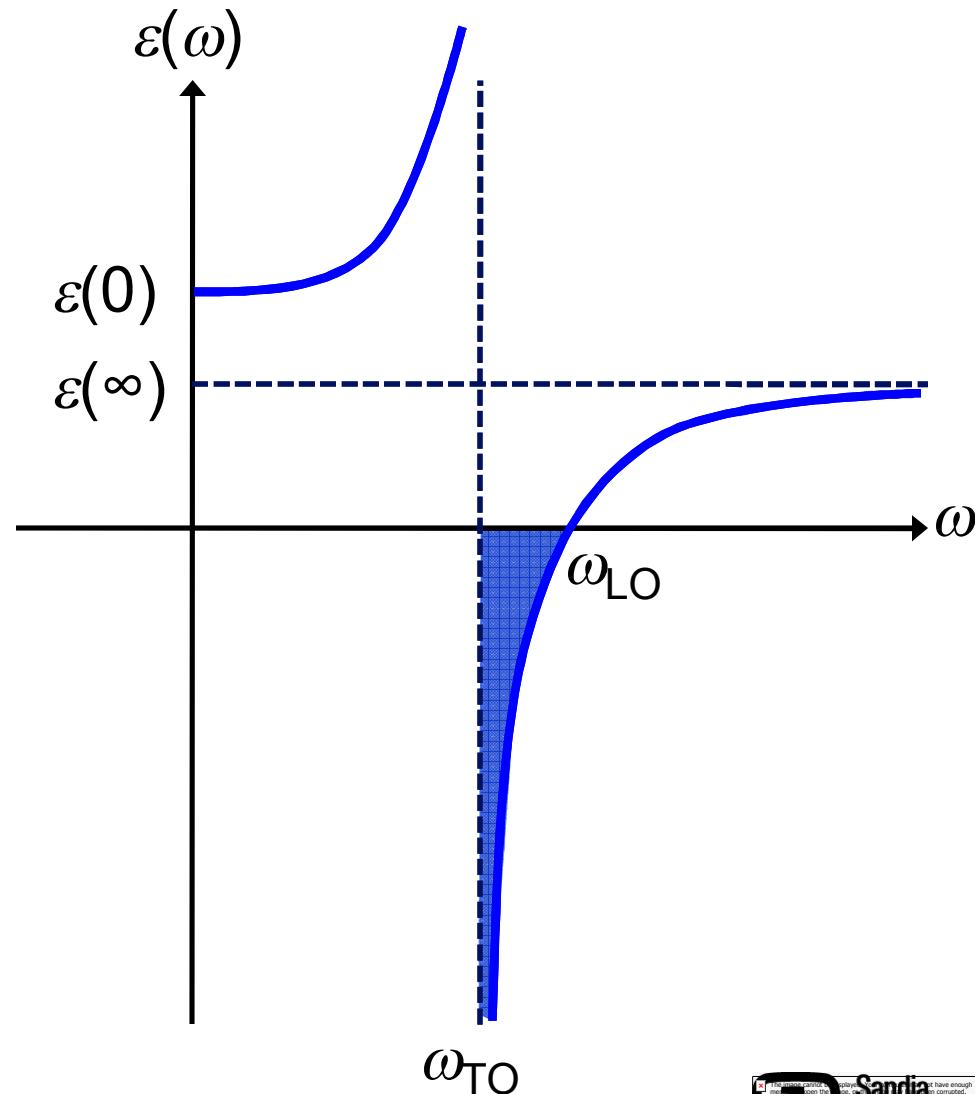




Alternative Low-Loss Materials

Polaritonic (Reststrahlen) Materials

- All ionic or partially ionic materials
- Strong phonon-photon coupling in IR
- Negative permittivity between *TO* and *LO* modes
- Can tune frequency through atomic mass or bonding





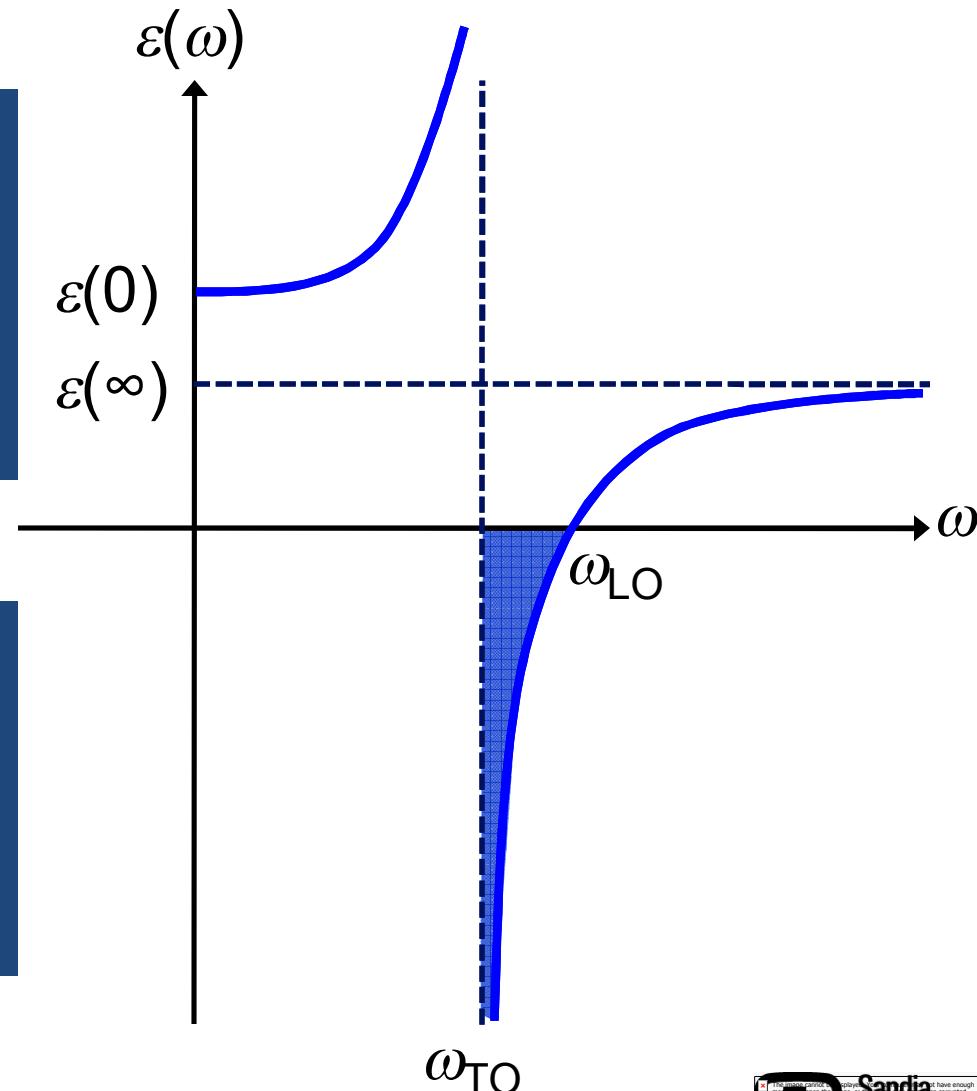
Alternative Low-Loss Materials

Desired Properties

- Strong interaction with electromagnetic waves
- Low dissipation
- Compatible with lithography

Potential Alternative Materials

- Many materials with *Reststrahlen* bands that span the MIR
- *Structure-property relations?*

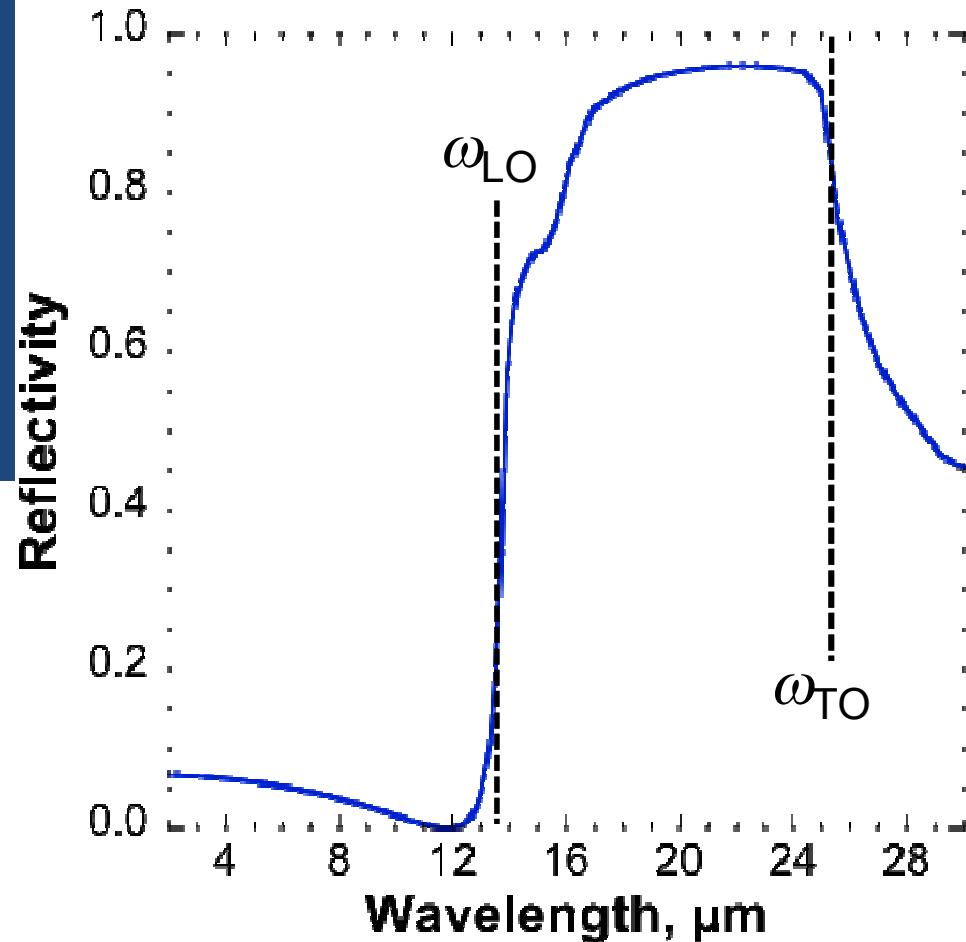


Structural Effects on IR Response

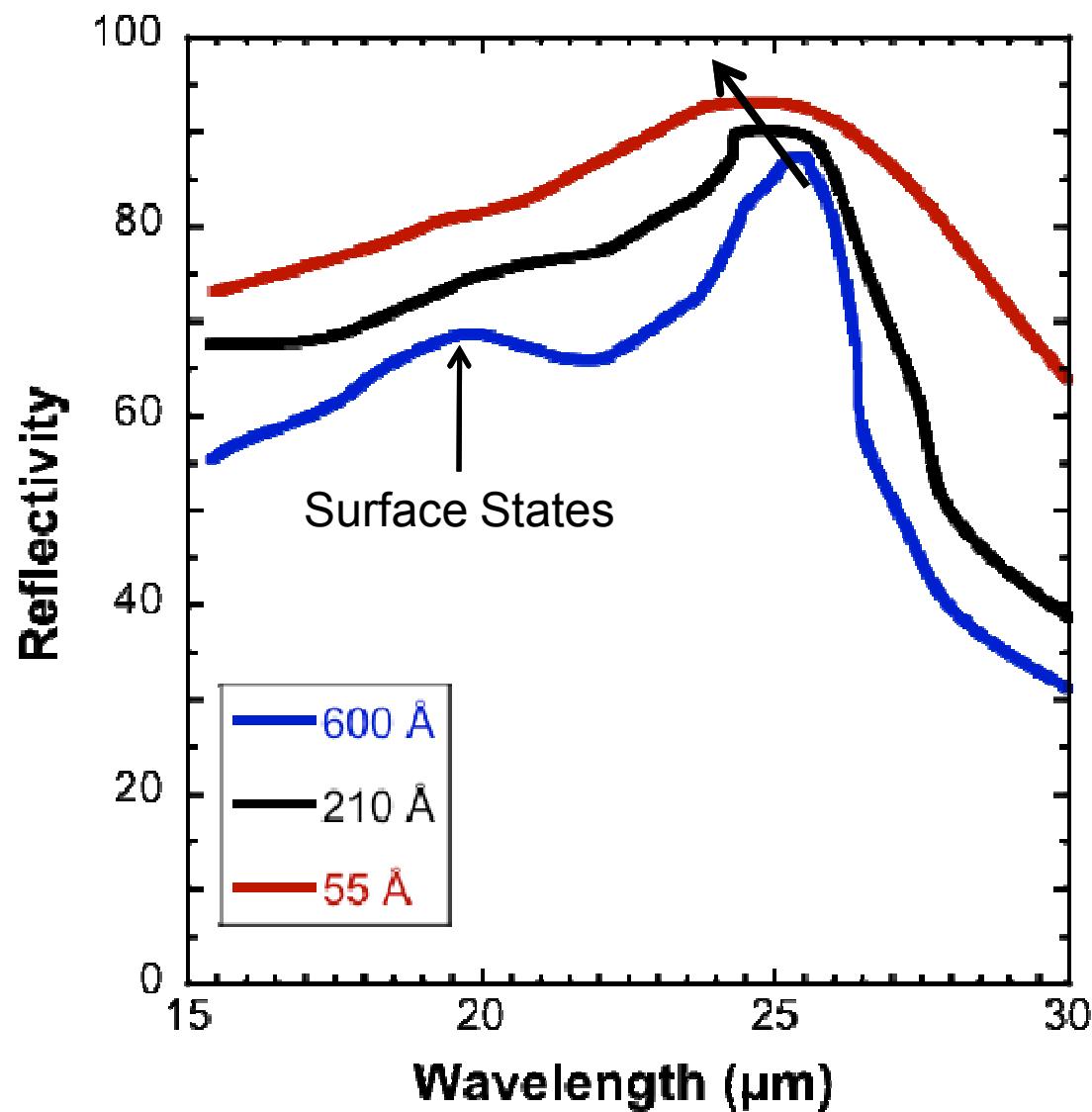
Model System: MgO

- *Reststrahlen* Band 15-25 μm
- Simple structure and two ion basis
- Simple phonon dispersion
- Multiple methods to control crystallinity

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Particle Size Effects on IR Response of MgO



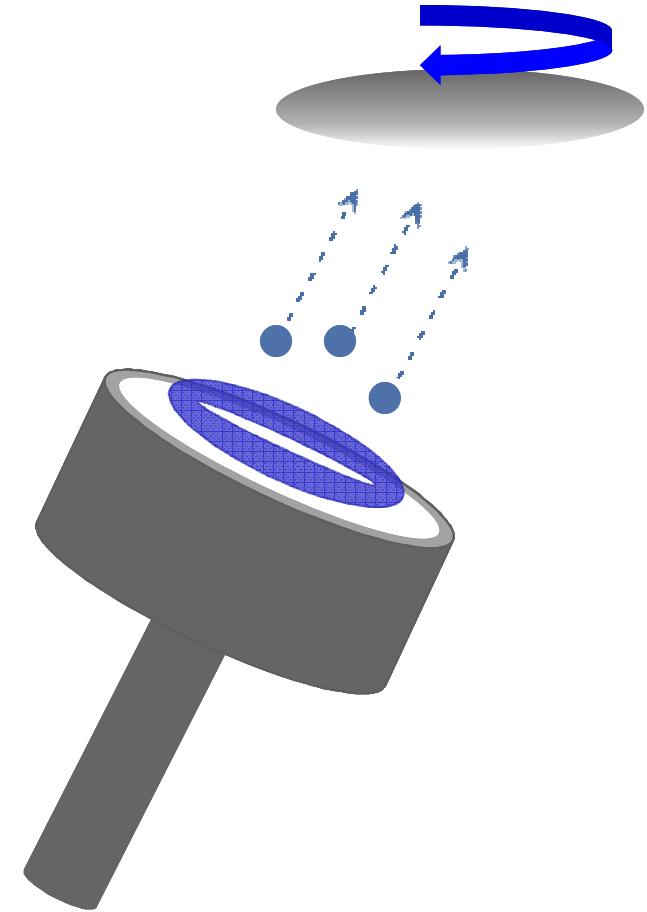
Particle Size Effects

- Reduced particle size broadens *Reststrahlen* response
- Apparent shift in peak reflectivity (ω_{TO})
- Surface modes present



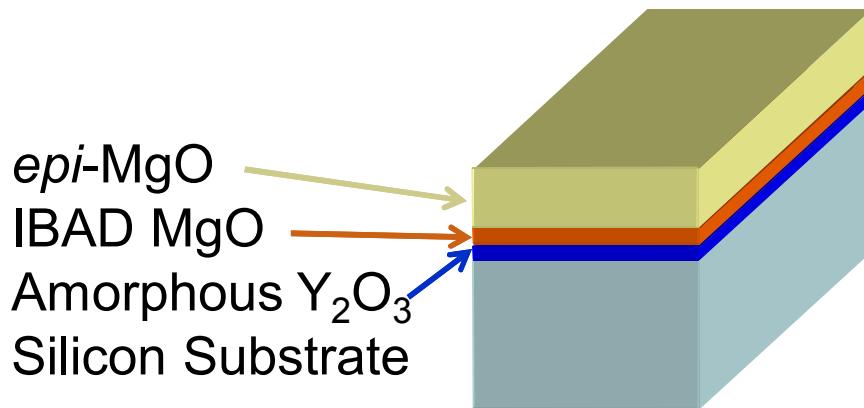
MgO Crystallinity Modification

- 200 nm thick films deposited by RF sputtering on 001-silicon
 - 30° off-axis geometry
 - Argon atmosphere
 - Room temperature substrate
- Thermal anneals used to modify grain/crystal size
 - 200-800°C in air × 1 hour

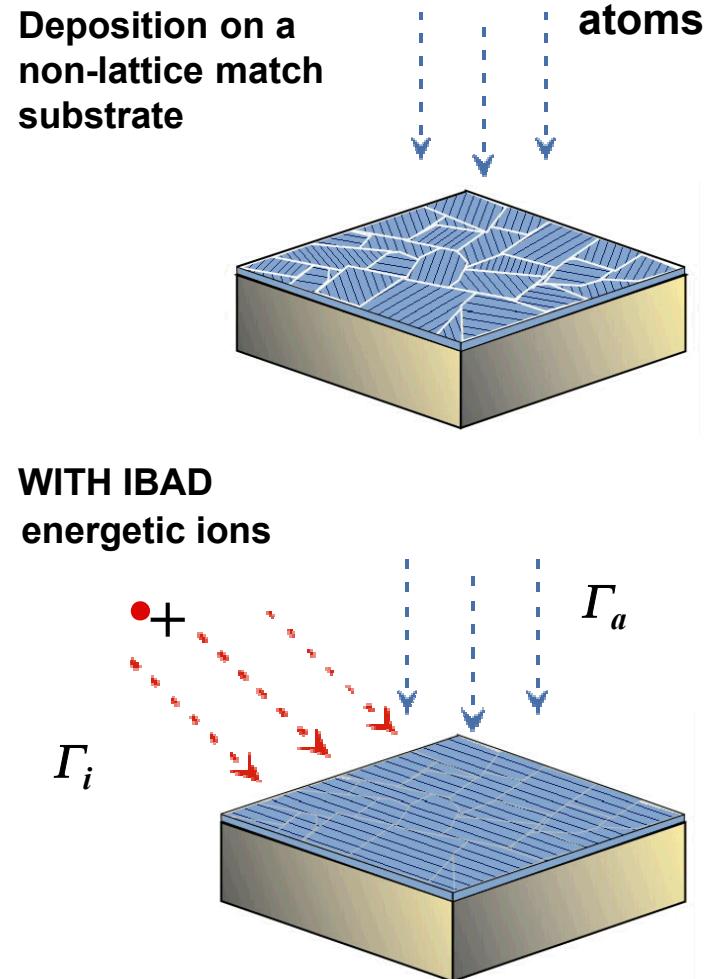


MgO Crystallinity Modification

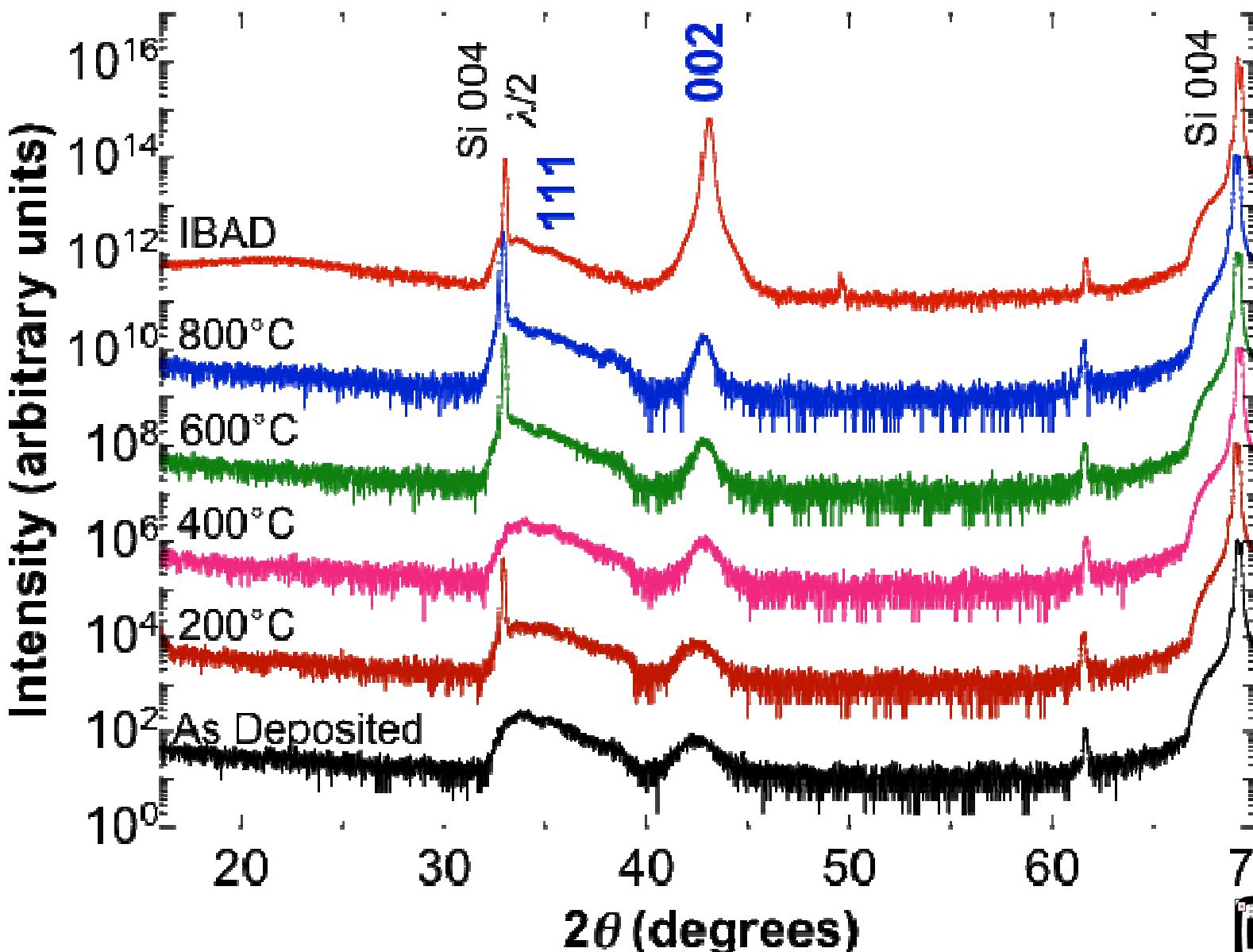
- Ion-beam assisted deposition
 - (001)-textured material



- $\Delta\omega_{002} \sim 1.2^\circ$
- $\Delta\phi_{220} \sim 4.7^\circ$



MgO Structural Properties





Microstructure Characterization

As-Deposited

As-Deposited

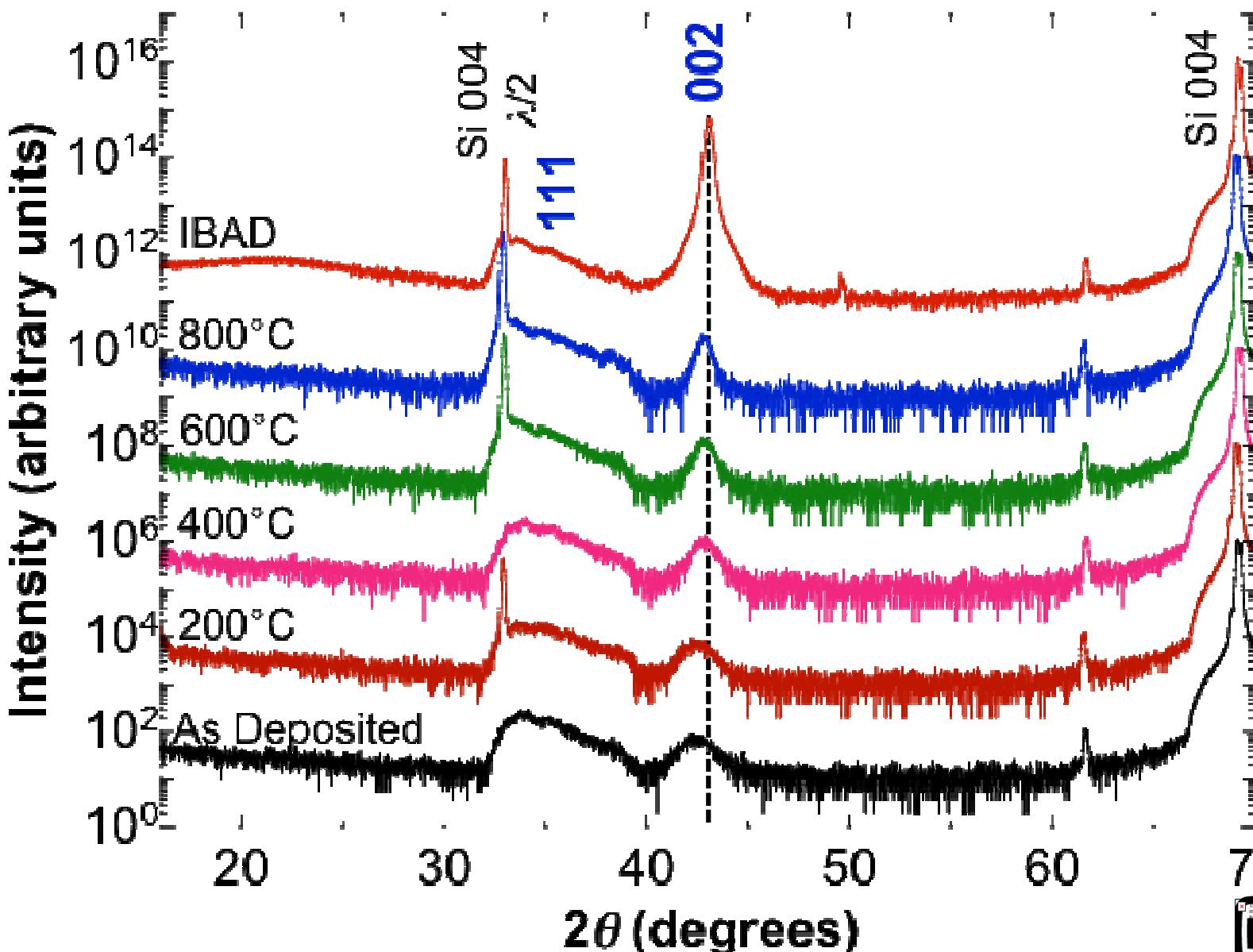
400°C

800°C

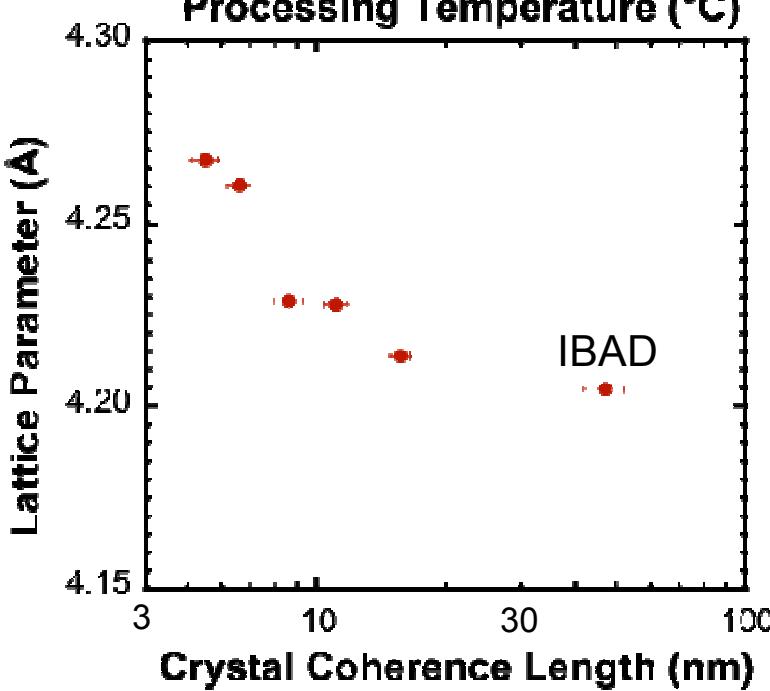
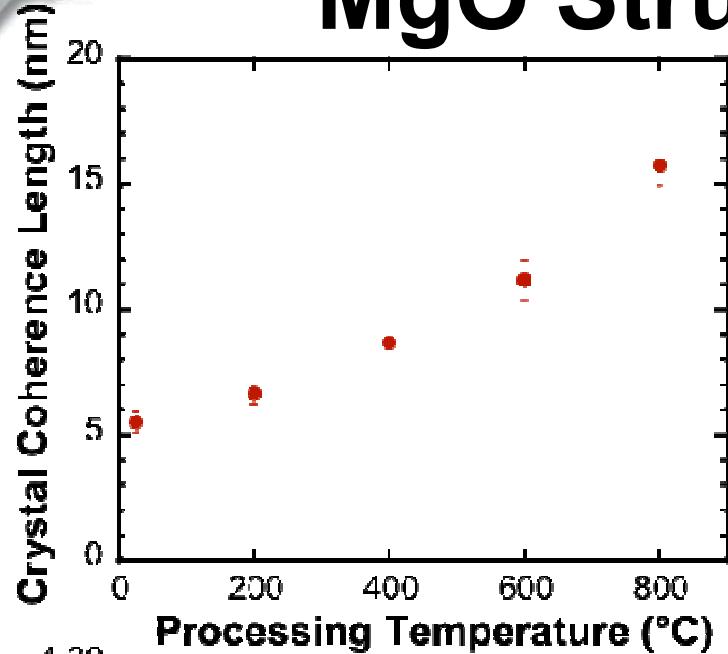
Particle Size Effects

- Dense microstructure
- Columnar morphology
- No change in apparent grain size with process temperature
 - ~ 75 nm
 - 6.8 ± 0.3 nm roughness

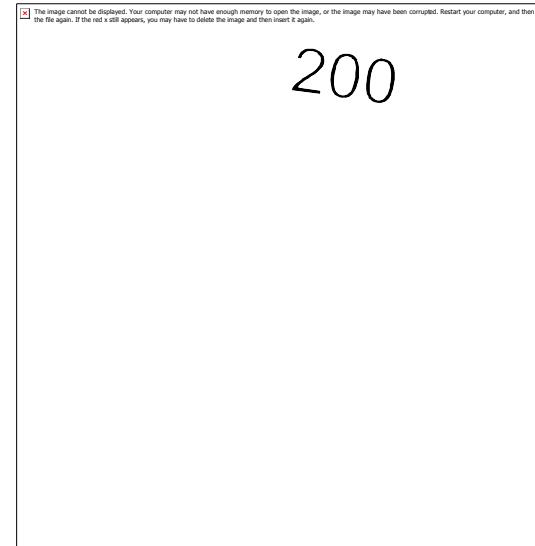
MgO Structural Properties



MgO Structural Properties



- Strong scattering dependence on processing temperature
- Lattice parameter decrease with crystallinity*
 - Increased grain/subgrain boundary area
 - High degree of disorder



* $\cos^2\theta / \sin\theta$ height error correction
P. Scherrer, *Nachr. Ges. Wiss. Goettingen, Math. Phys.*, **2**, 96 (1918)
J.F. Ihlefeld, et al., *Appl. Phys. Lett.*, **97**, 191913 (2010)



Dark-Field and High-Res TEM

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As-Deposited

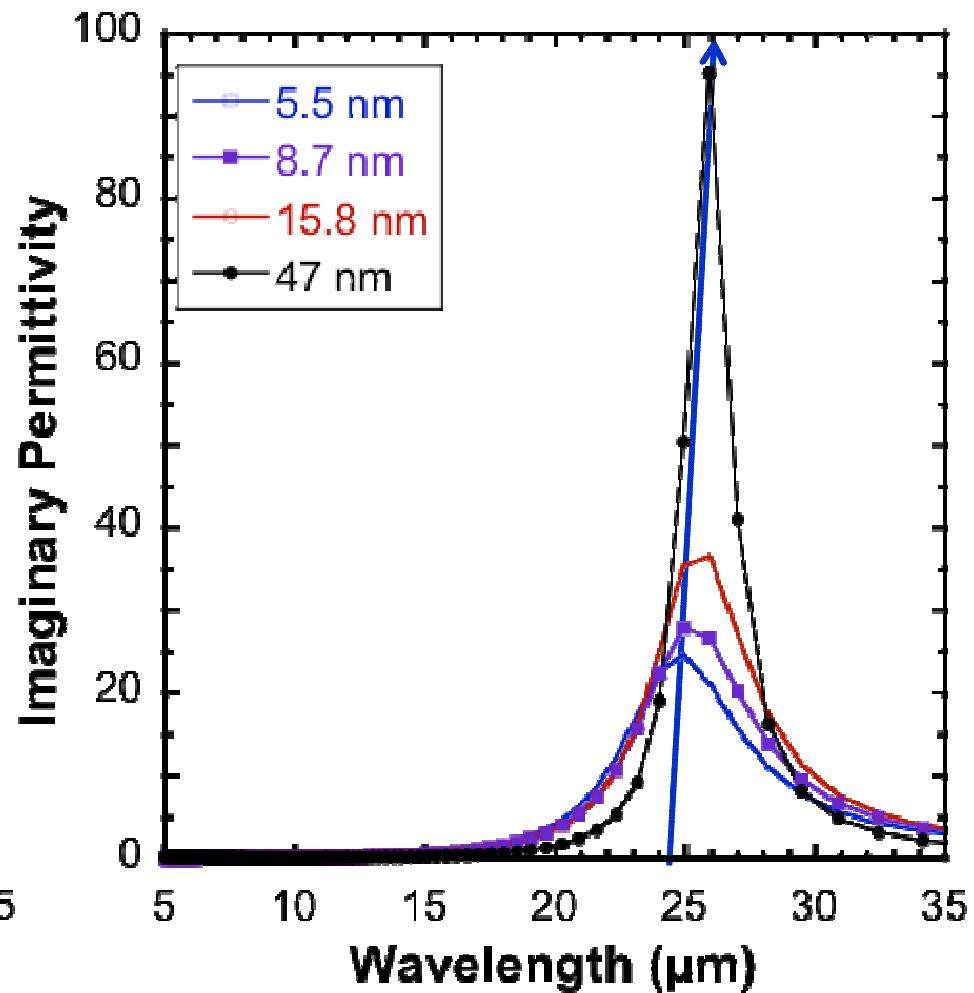
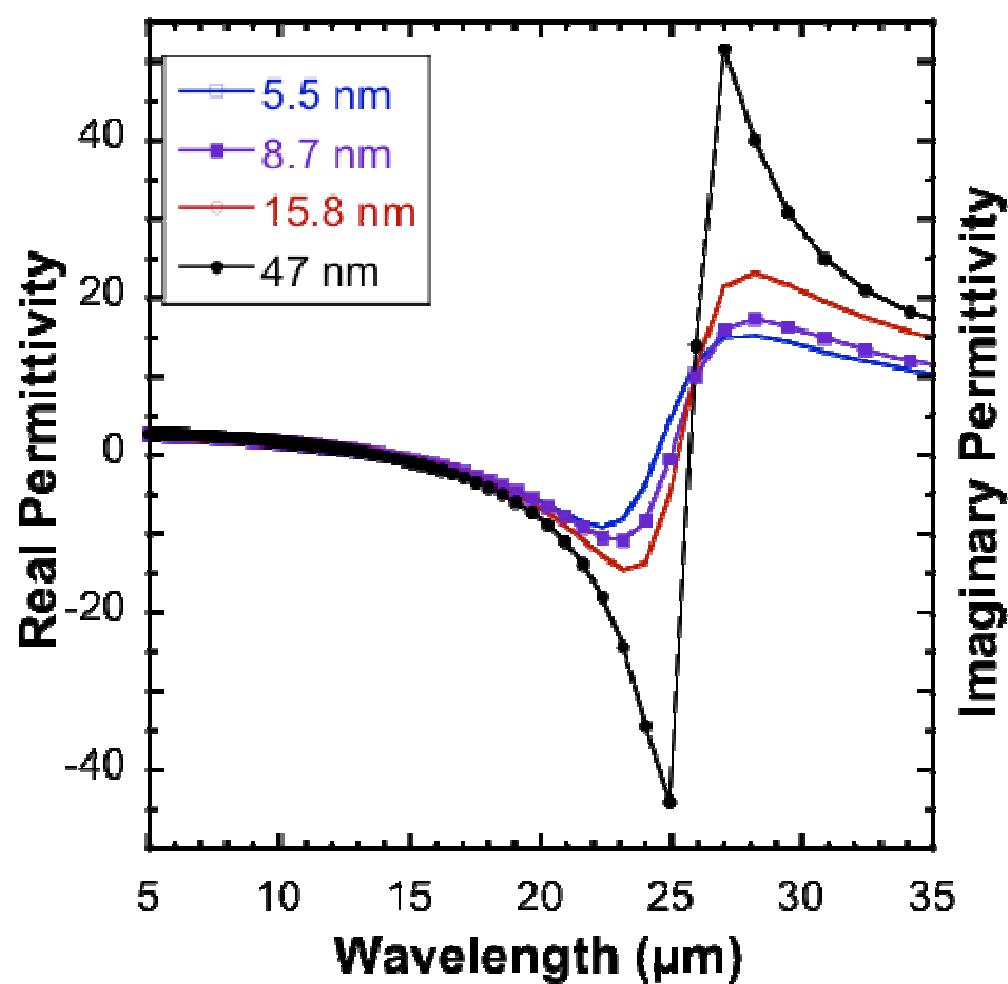
400°C

800°C

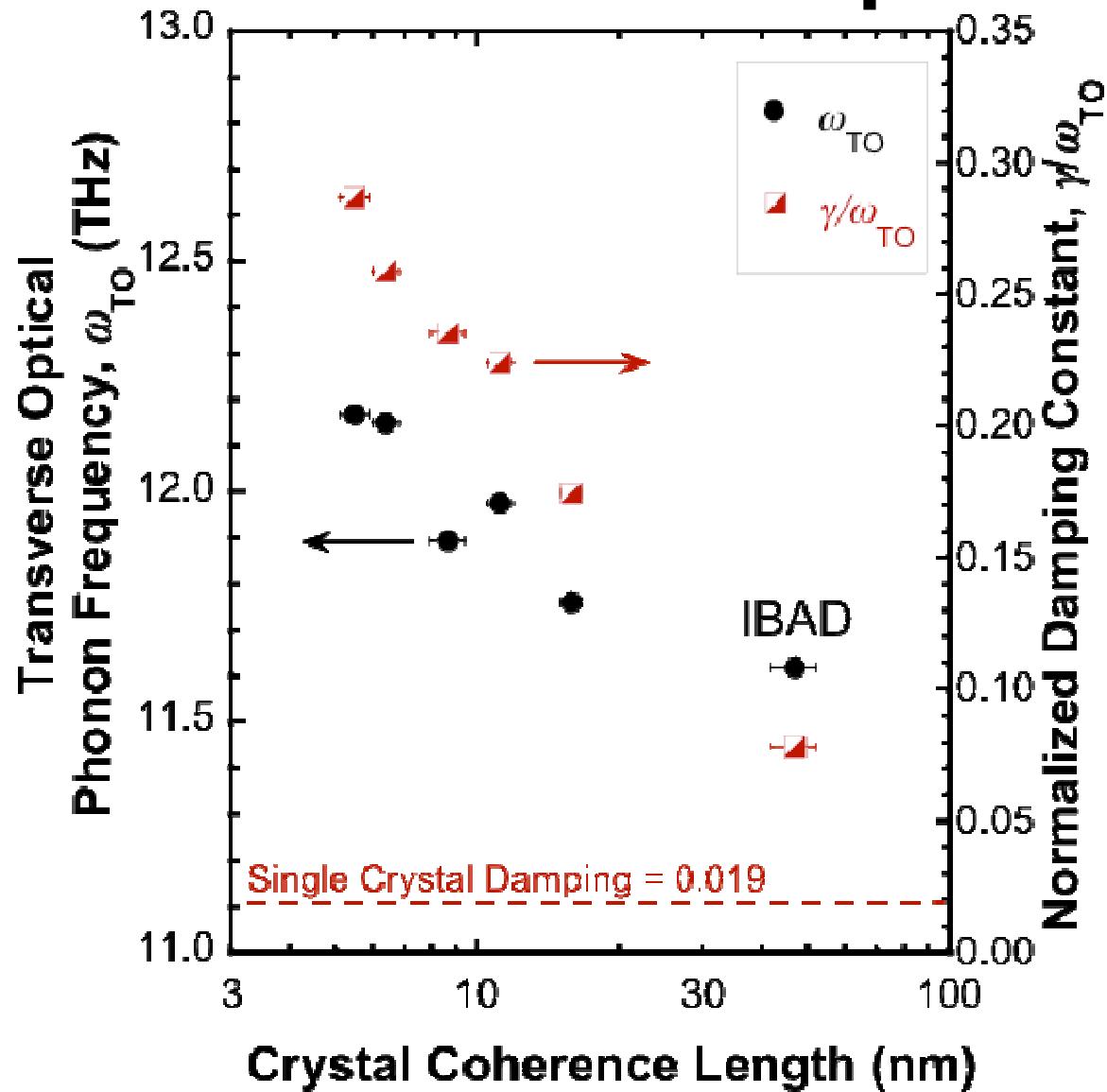
As-Deposited



MgO Optical Properties



Crystallinity Effects on IR Response



- Response fit with modified classic oscillator model:

$$\varepsilon(\omega) = \varepsilon_{\infty} + \left[\frac{\varepsilon_0 - \varepsilon_{\infty}}{1 + \left(\frac{\omega^2}{\omega_{\text{TO}}^2} \right)} - i \left(\frac{\omega\gamma}{\omega_{\text{TO}}^2} \right) \right]$$

- Crystal coherence has strong effect on phonon damping constant
- Shift in ω_{TO} concomitant with lattice parameter



Summary

- Crystallinity modified by thermal treatments
- Optical response strongly dependent on crystal coherence
- Increased damping with increased disorder
- Transverse optical phonon mode frequency correlates with lattice parameter
- May have broad implications for IR metamaterial design
 - Epsilon-near-zero materials
 - Reduced dimensions of resonators ($\lambda/10$)



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Three Primary Optical MM Limitations

1. Metallic Resonators

- Ohmic losses
- Broad and weak resonances
- Less interaction with light approaching visible frequencies

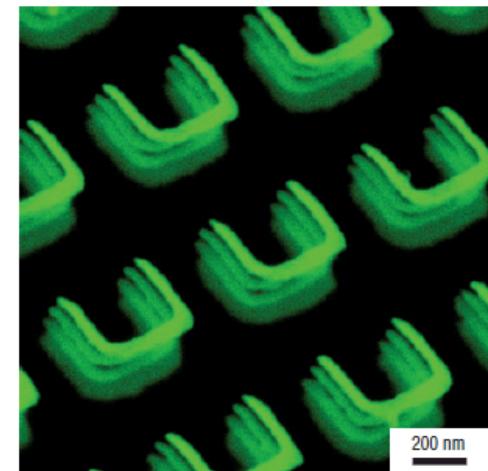
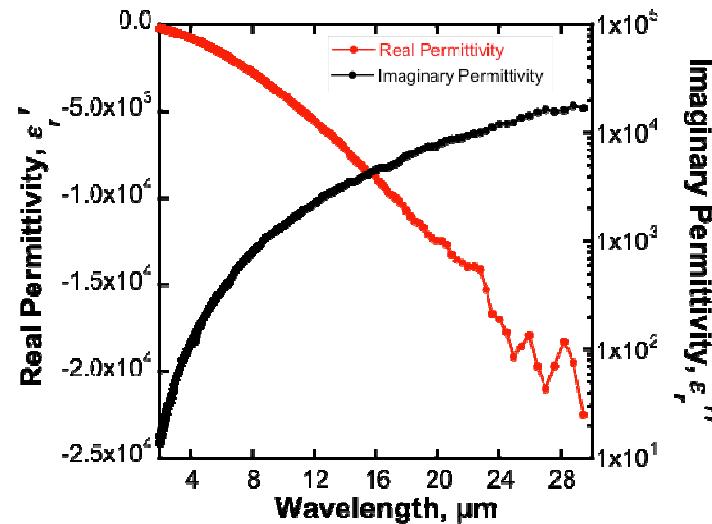
2. Anisotropic Response of Metallic Resonators

- Magnetic responses require off-axis excitation

3. Fine scale features

- Requires high-end e-beam lithography
- Limitations for large size samples

Need a design approach that mitigates each of these three issues



Giessen- Nat. Mater. 7, 31, (2008)

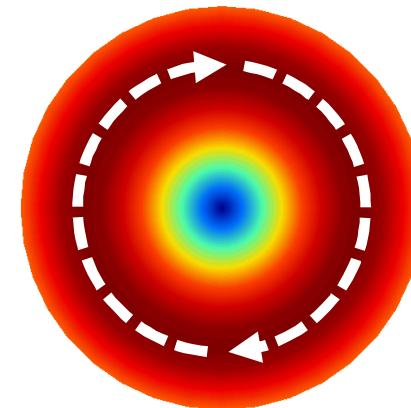


Spherical Dielectric Resonators

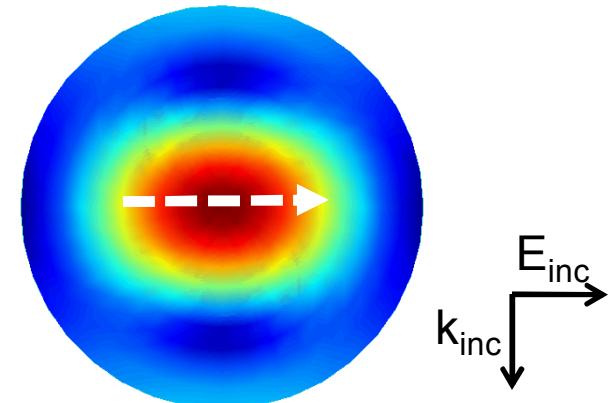
Alternative Means of Achieving Response

- All dielectric materials
 - No electron currents
 - Displacement current
 - Electronic polarization currents
- Spherical (Mie) resonators can provide the desired response
 - Isotropic response
 - Supports both magnetic and electric resonances (dependent upon composition and geometry)

Magnetic mode



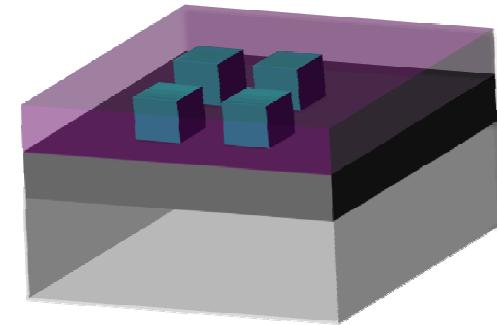
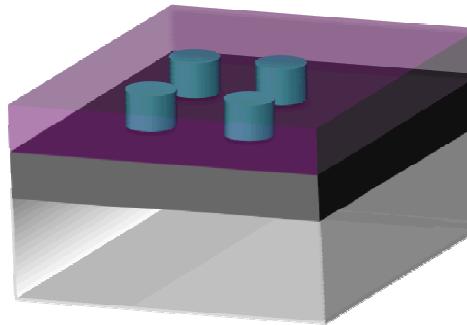
Electric mode



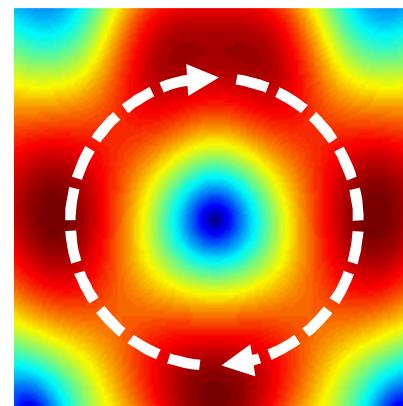


Cubic Dielectric Resonators

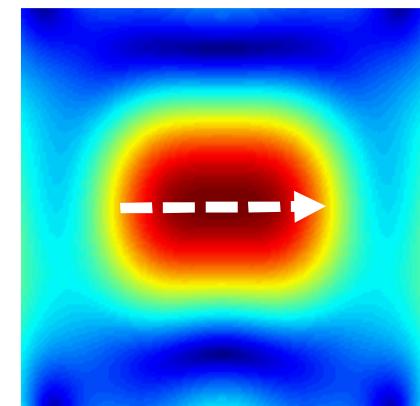
- Spherical components not compatible with standard lithography
- Cubic resonators maintain optical isotropy ($m3m$ symmetry)
 - No ohmic loss
 - Can be easily integrated into multi-layer composites (through planarization)
 - Satisfies issues with metallic elements



Magnetic mode



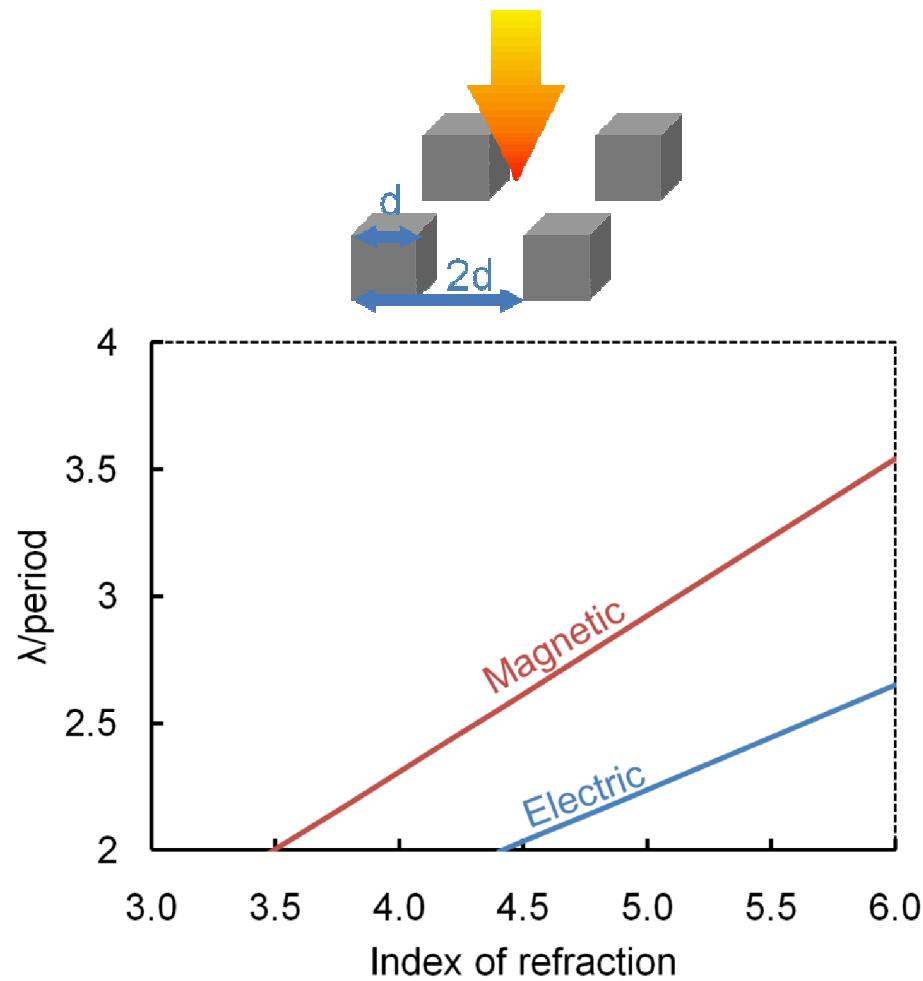
Electric mode



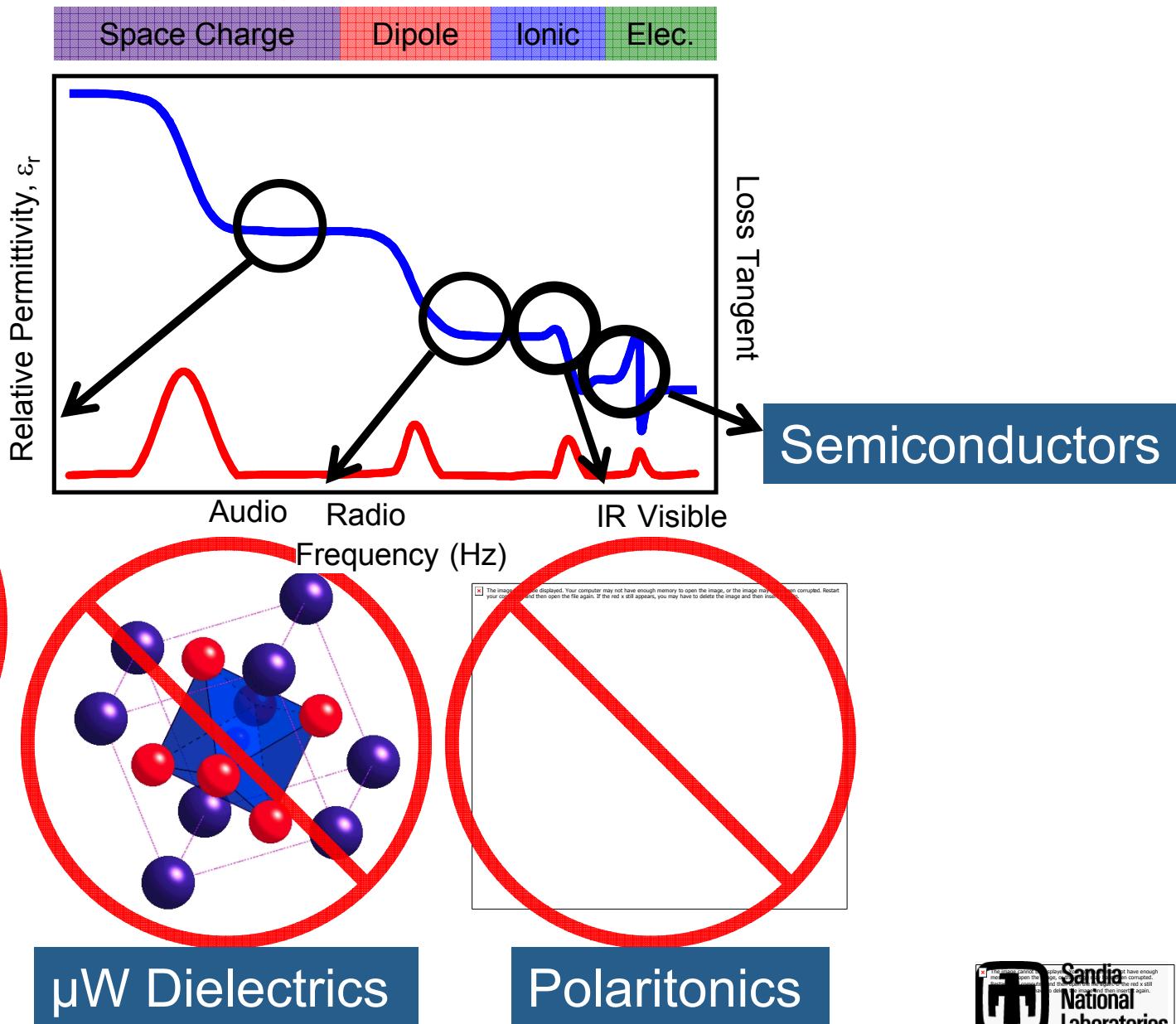
E_{inc}
 k_{inc}

Resonance Behavior

- Mie theory not directly applicable to cubic resonators
 - Modeled via rigorous coupled wave algorithm package (GDCALC)
- Distinct resonances
 - Lowest frequency is magnetic (TM)
 - Second resonance is electric (TE)
 - Resonances scale with the dimensions and refractive index



Identifying Ideal Materials





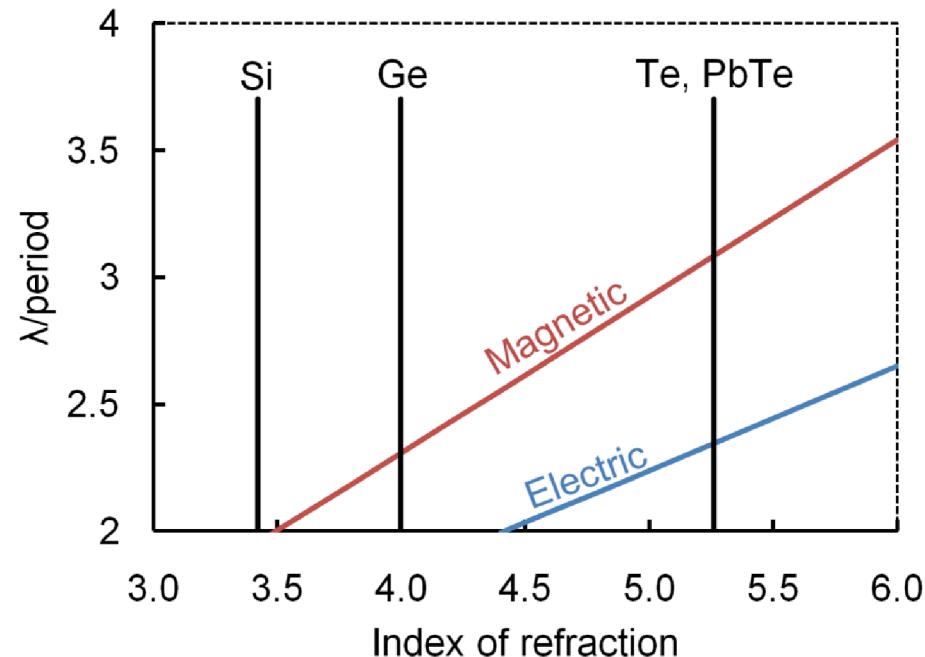
Identifying Materials

Desired Properties

- High refractive index
- Low loss
- Compatible with lithography

Potential Alternative Materials

- Narrow band-gap materials (Ge, Te, PbTe, etc.)
- High-index
- Low-loss below the bandgap

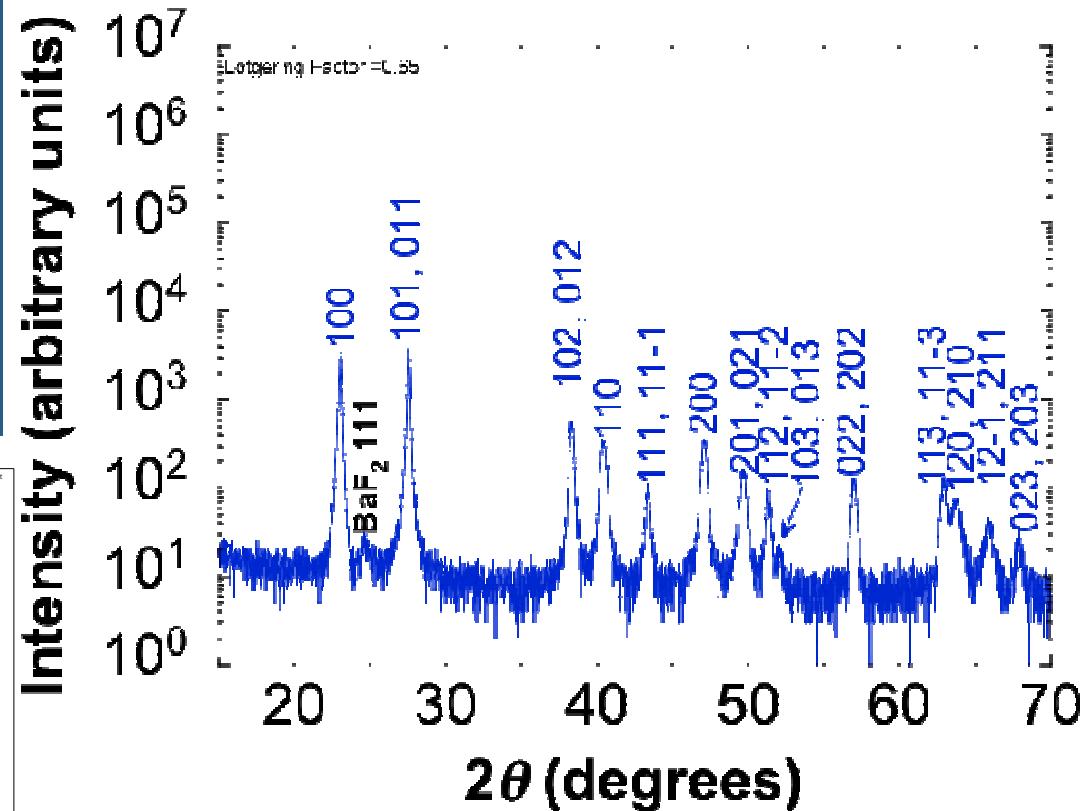




Optimized IR Resonators

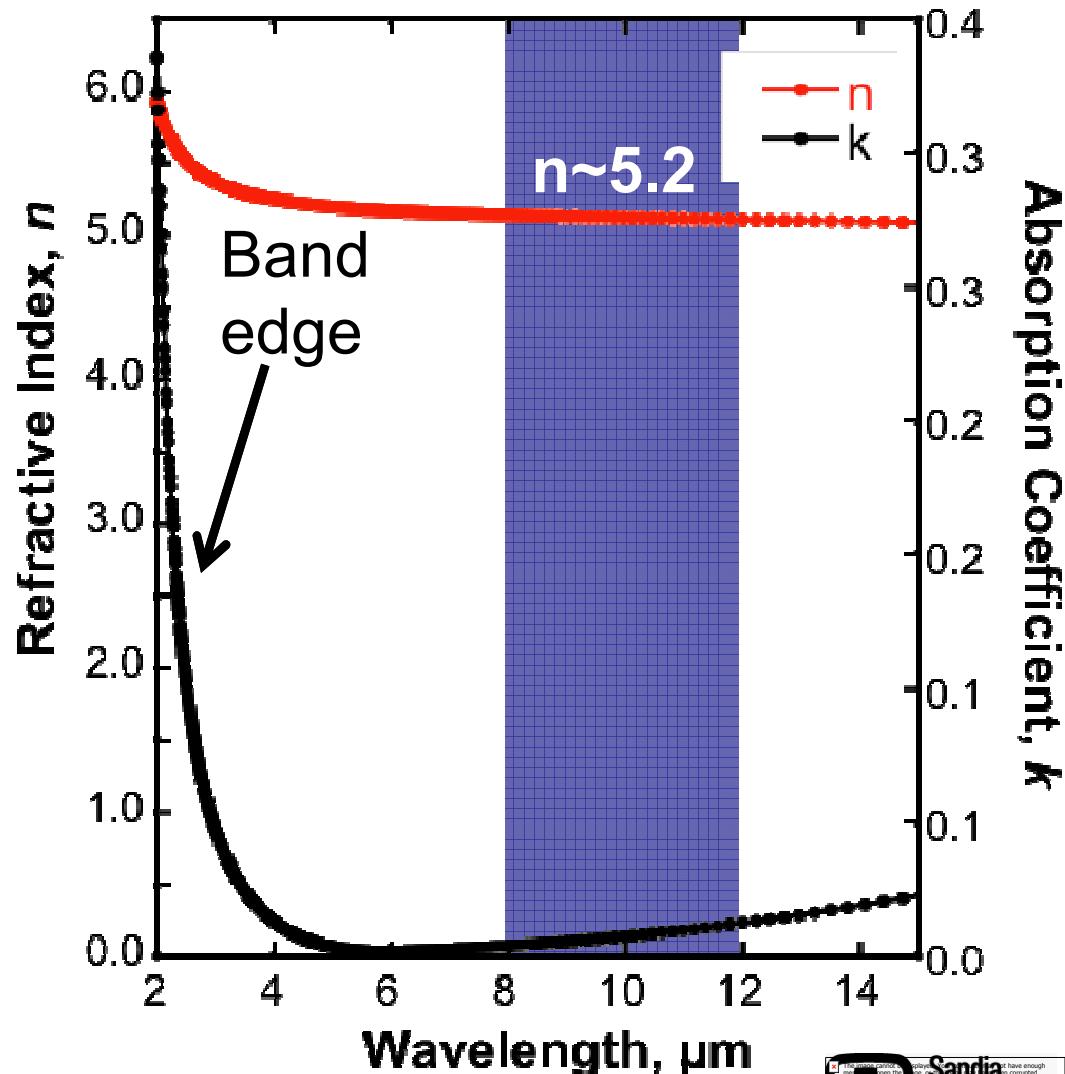
- Tellurium grown via electron-beam evaporation
- Room temperature growth
- Single Crystal BaF_2 substrate

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Optimized IR CDR

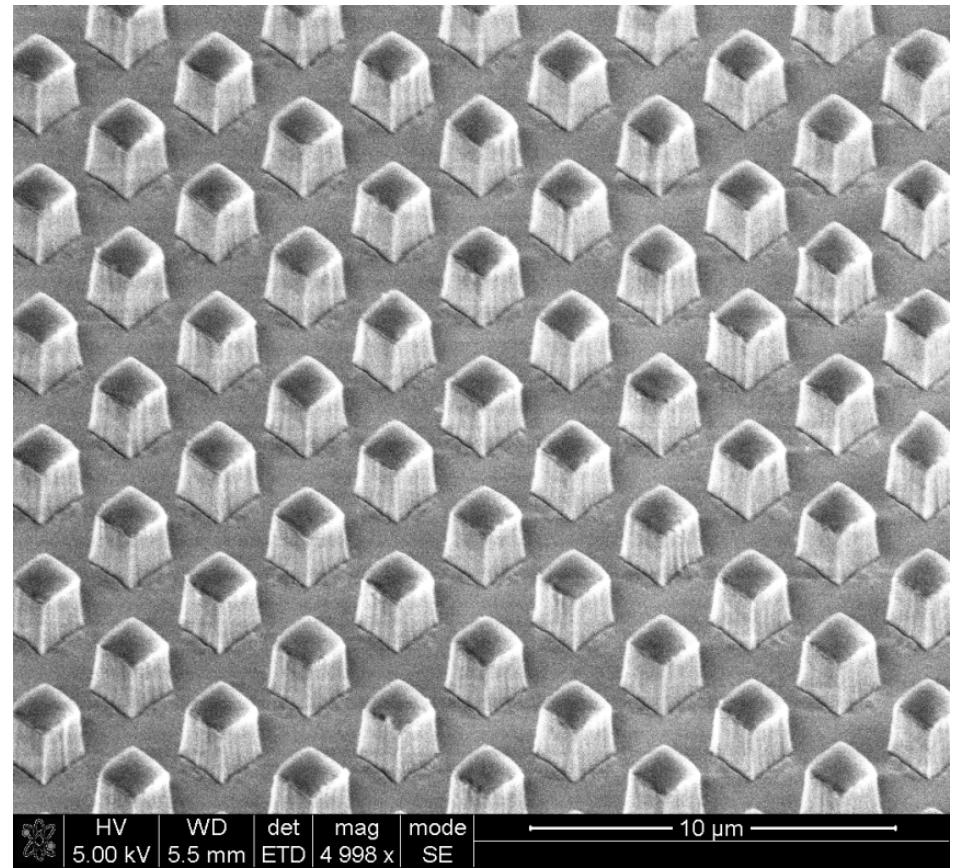
- Te has $P3_121$ symmetry
 - Polycrystalline required for isotropy
- Measured $n = 5.02 + 0.04j$ @ 10 μm
 - Polycrystalline average = 5.3
- BaF_2 substrate
 - Transparent to 10 μm
- 1.7 μm Te cube will have magnetic resonance at 10 μm





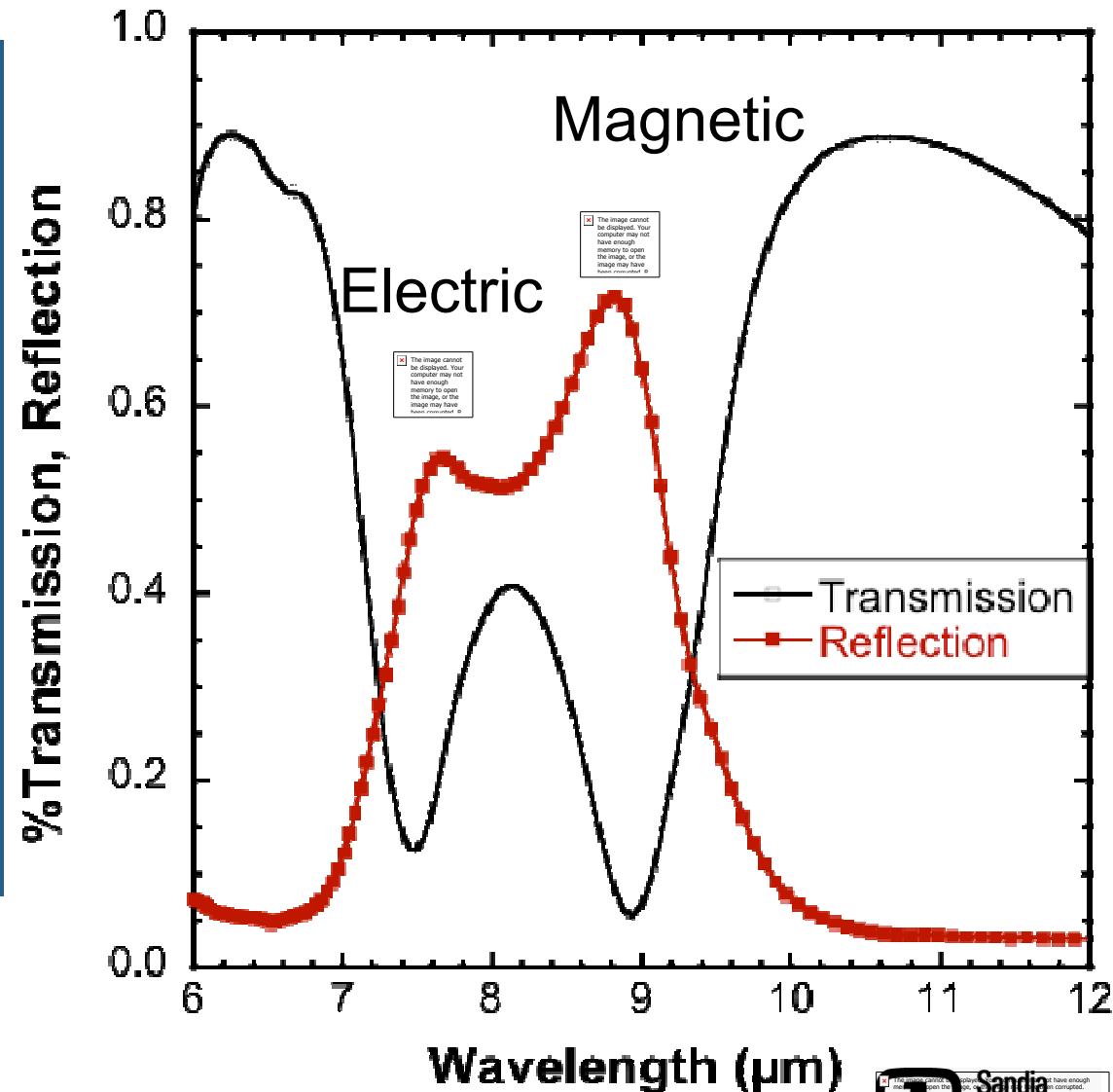
Fabrication of the CDR

- 1.7 μm Tellurium film deposited onto 1" BaF_2 wafer
- Patterned via e-beam lithography
 - Patterned area = 1 cm^2
- Cubes etched using a reactive ion etching process
 - Excellent uniformity over the array
 - Some over etching
 - Base of 1.53 μm
 - 10° sidewall slope
 - Minor polymer redeposition



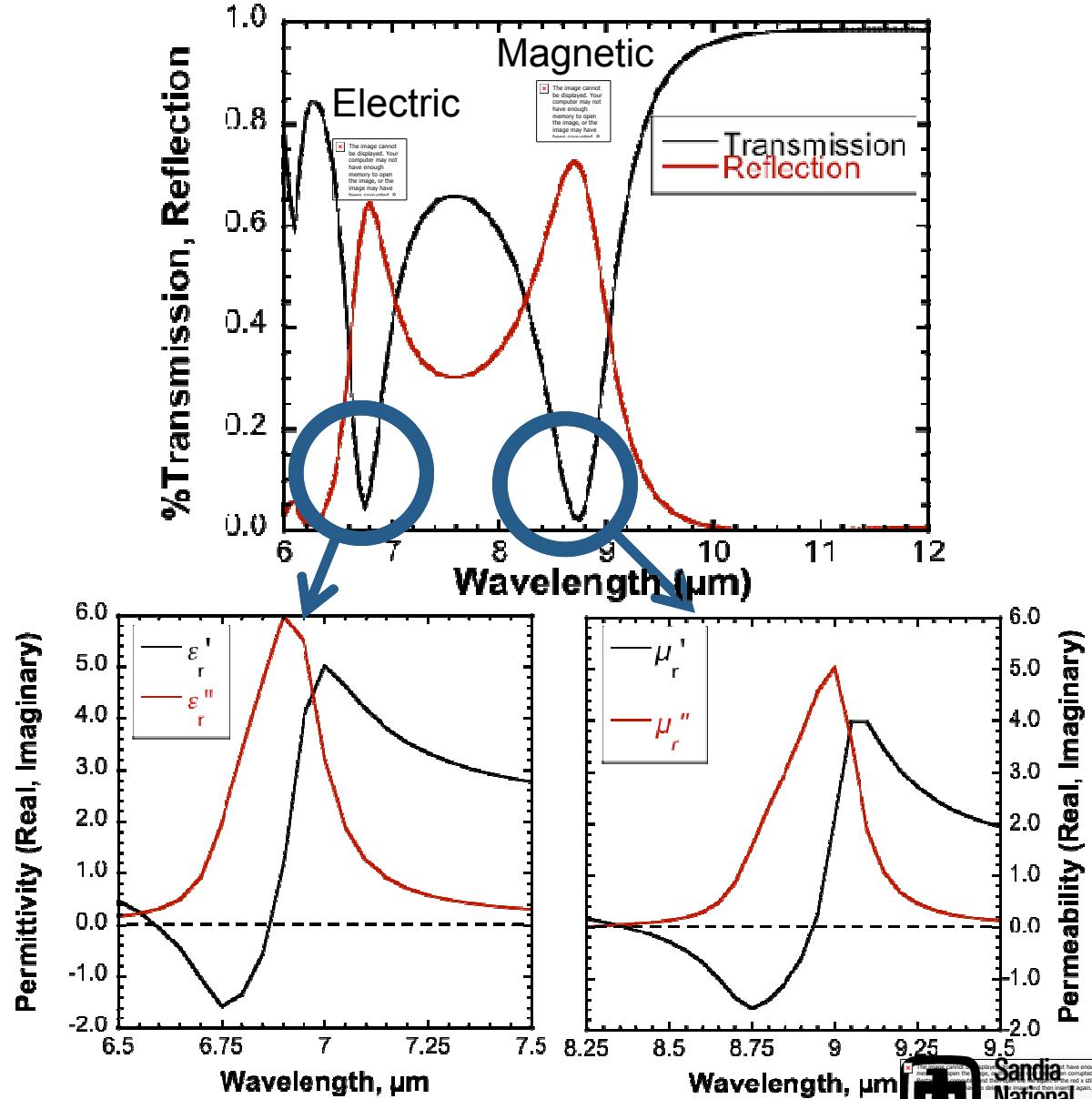
Optical Response

- Measured using a hemispherical directional reflectometer
- Both resonances are well defined and are present above the diffraction cut-off
- Loss ($1-R-T$) less than 8% between the resonances
- Data is not normalized
- *First demonstration of an all dielectric optical metamaterial*



Extracted Optical Properties

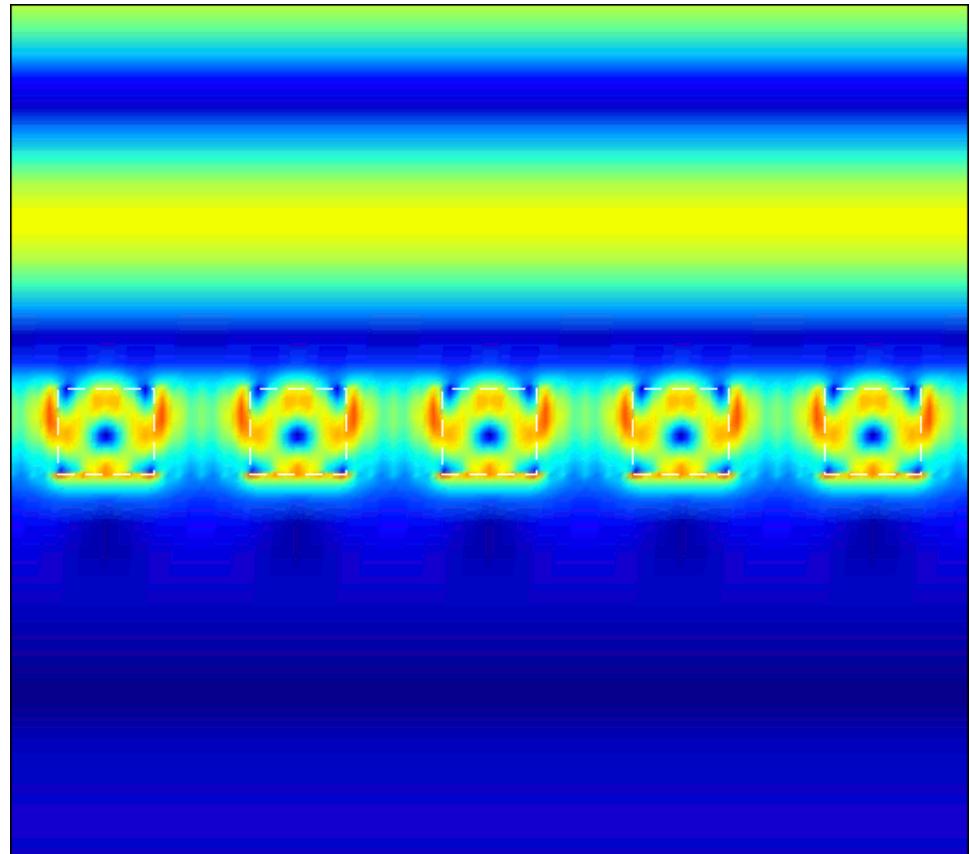
- Properties computationally derived averaging real cube dimensions
 - Reasonable agreement
- Permittivity and permeability extracted
 - Both values less than -1
 - Permeability loss is less than 0.5 when permeability is -1
- World's First known IR magnetic mirror***





Dielectric Resonator Summary

- Cubic resonator designed with magnetic and electric resonances in the IR for the first time
 - Low loss
 - Isotropic response
- Present efforts focus on improving quality of Te films and etching process
- Integrate into negative index constructs
 - Two intermixed resonators





Summary

- Multiple 3D IR metamaterial embodiments investigated
- An unconventional materials toolbox is being developed
 - Epsilon near zero materials
 - Dielectric resonators using narrow bandgap semiconductors
- Enabling low loss metamaterial preparation